

# Introduction to passivated contacts

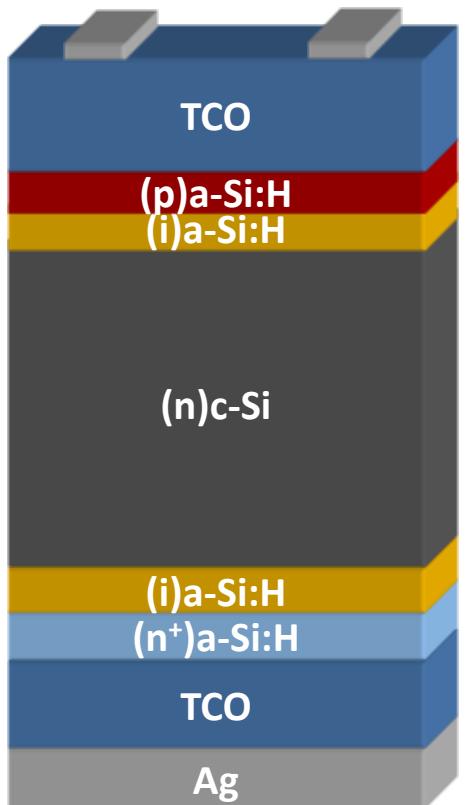
Lars Korte

Institute Silicon Photovoltaics

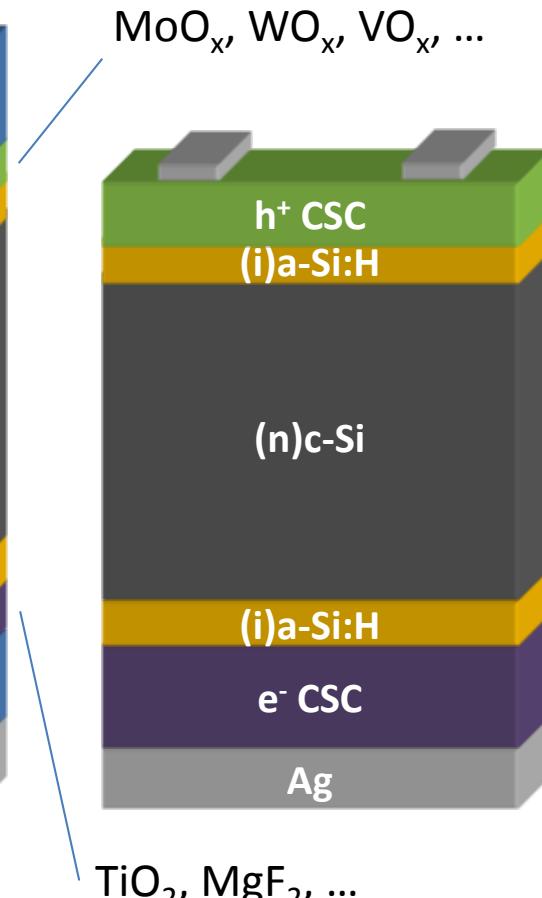
Passivated Contact Workshop  
Eindhoven, 31.1.2018

# Carrier selective contacts for c-Si solar cells

“classical” a-Si:H/c-Si  
heterojunction solar cell



CSC- based solar cells

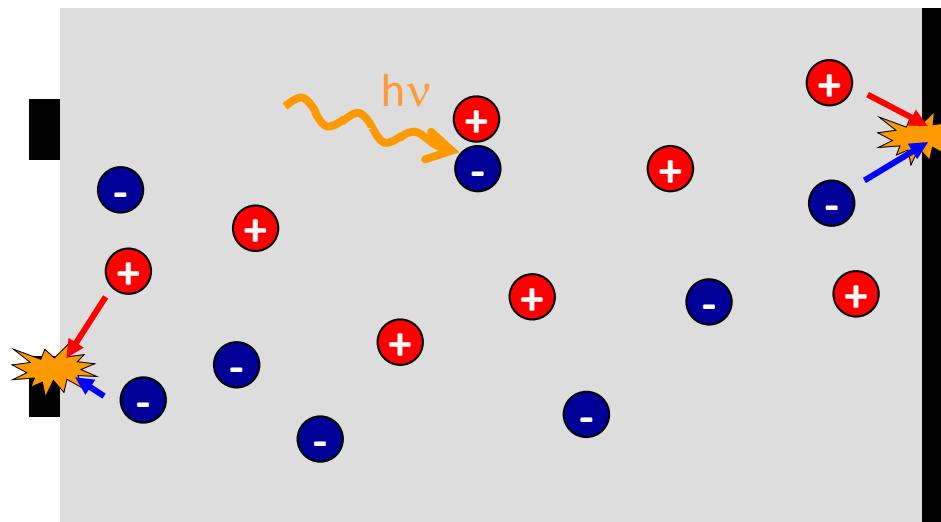
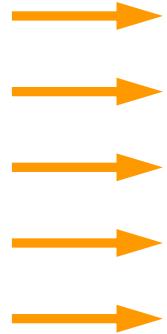


Replace doped layers by “carrier selective” layers

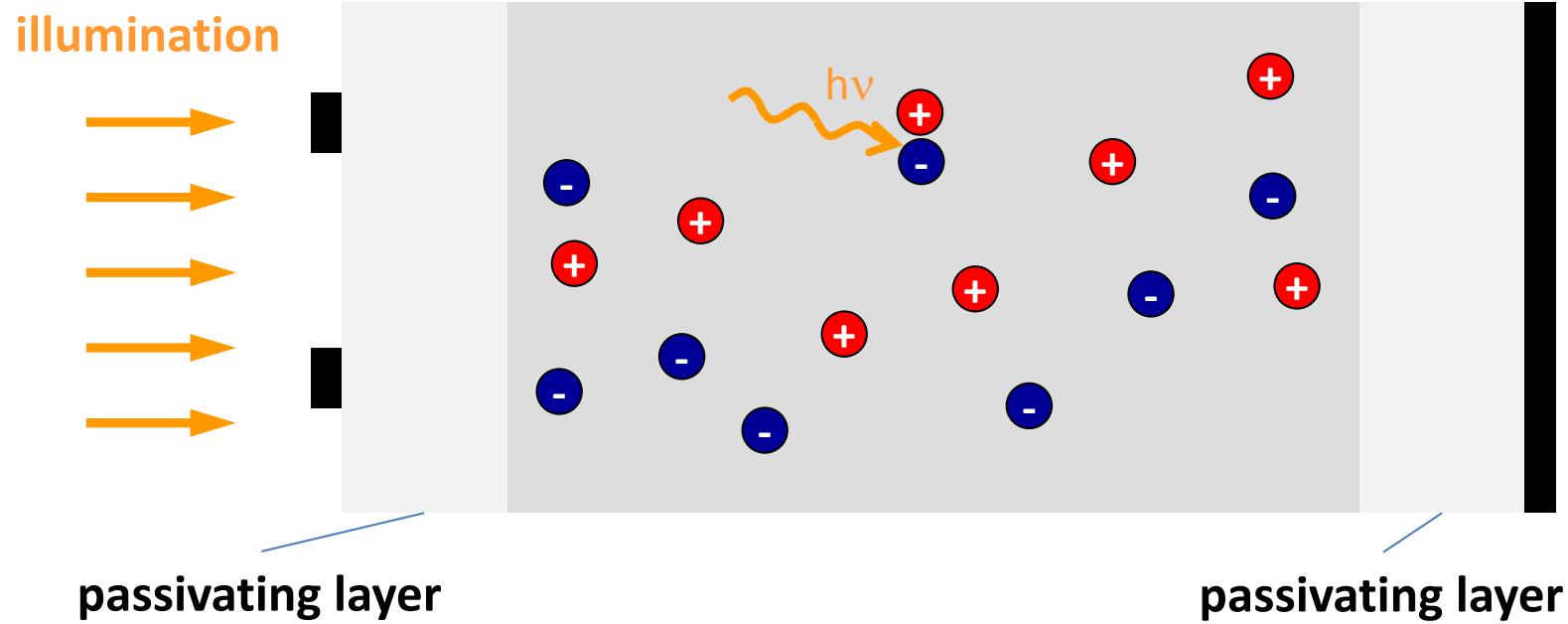
- Highly transparent front contact
- Might also replace TCOs if sheet resistivity is low enough (front), optics OK
- Even omit passivating layers (a-Si:H,  $SiO_2$ )?

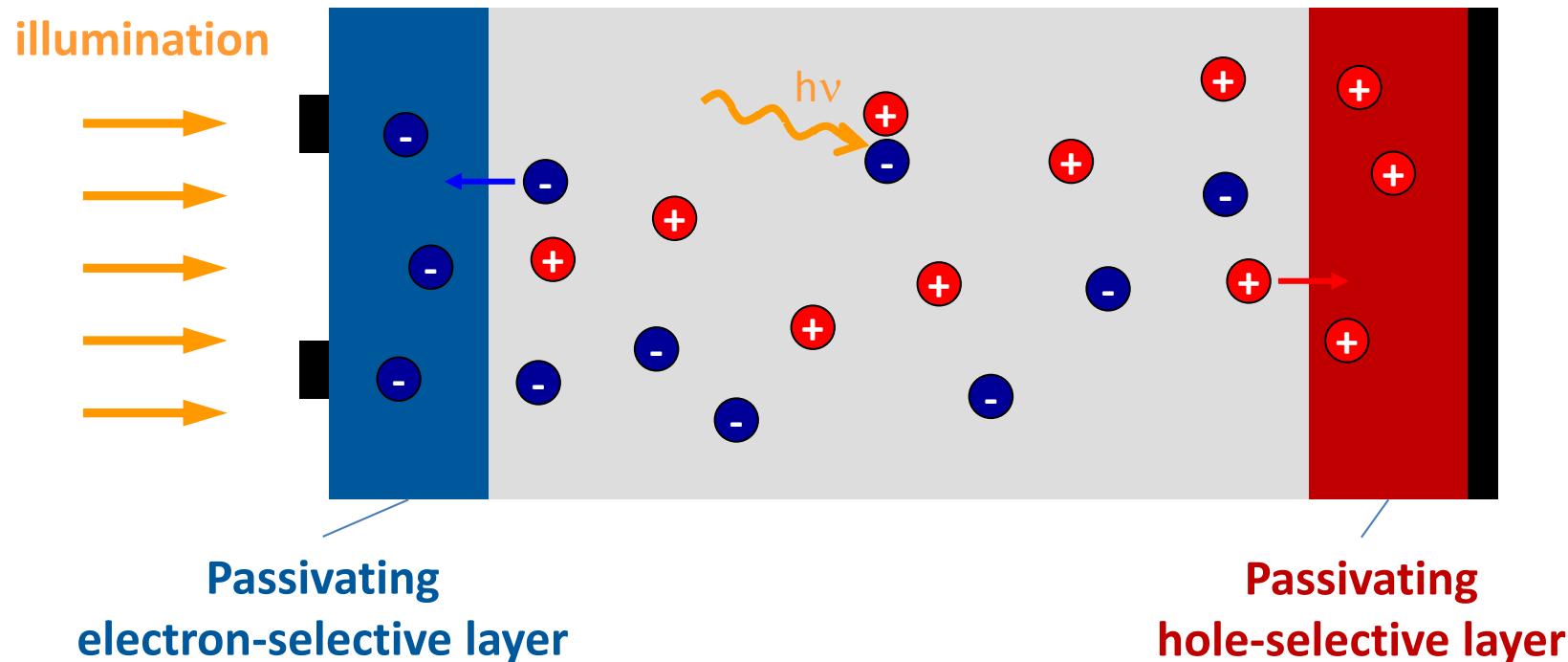
# Passivating contacts

illumination



# Passivating contacts

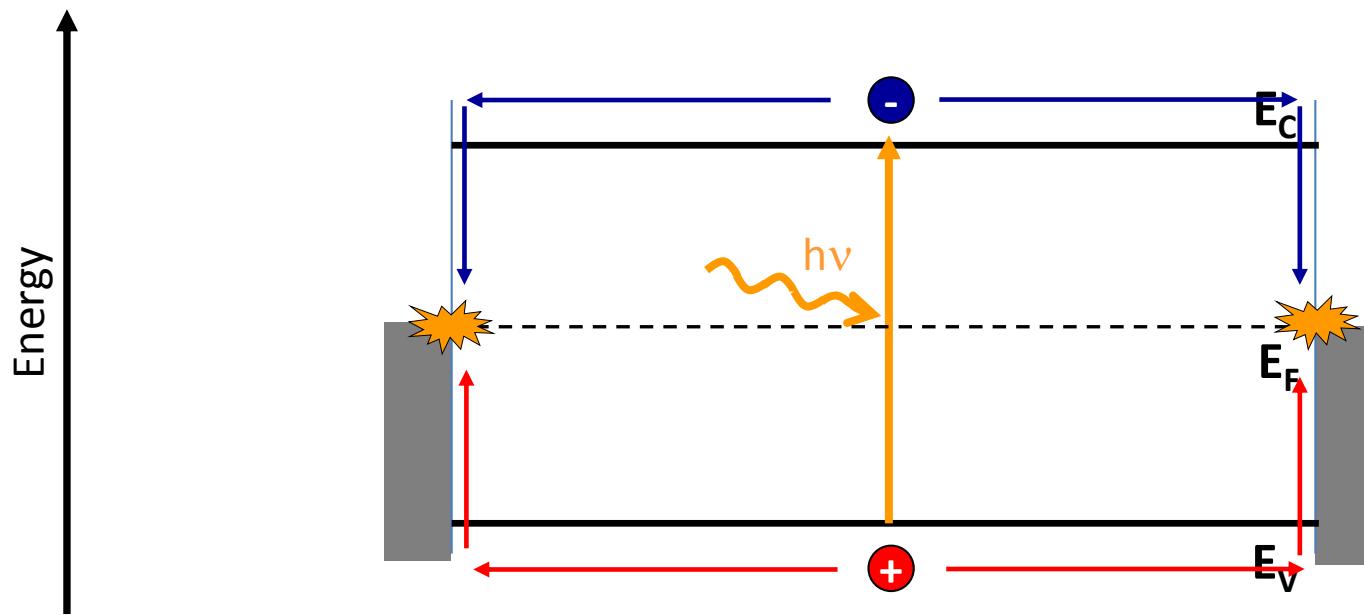
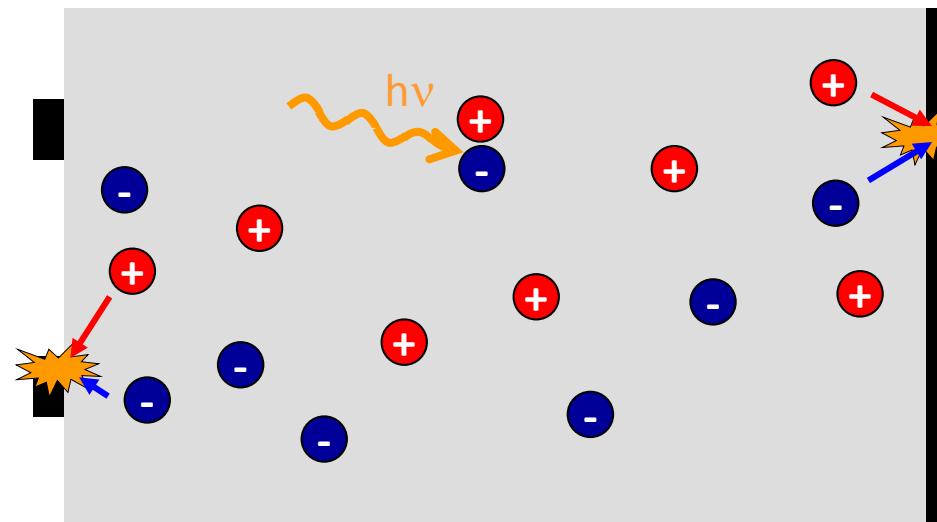
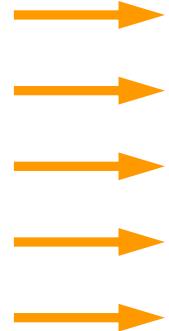




- What is a carrier-selective passivating contact (CSC)?
- “Classic” CSCs in silicon: amorphous/crystalline silicon heterojunctions
- Novel CSC example:  $\text{IWO}_x/\text{c-Si}$  – band line-up

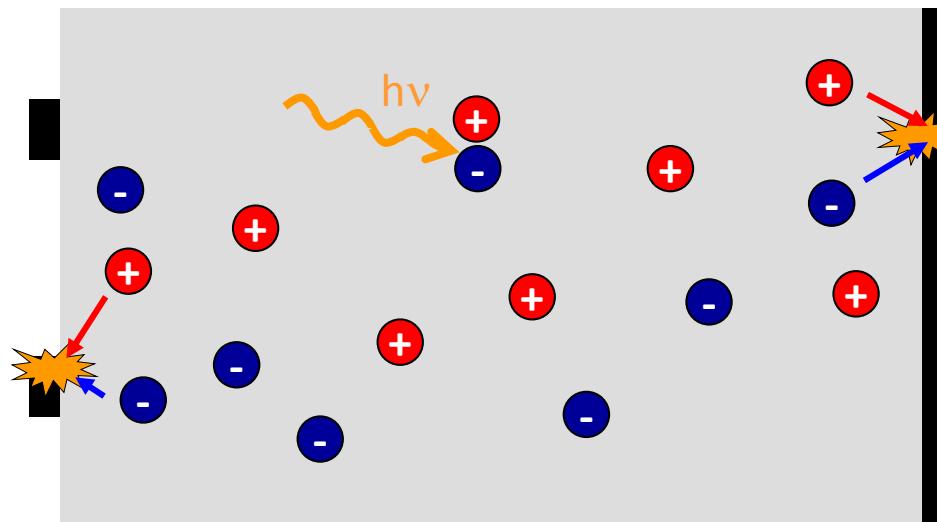
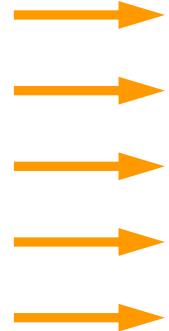
# Non-passivating, ohmic contacts

illumination



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illumination

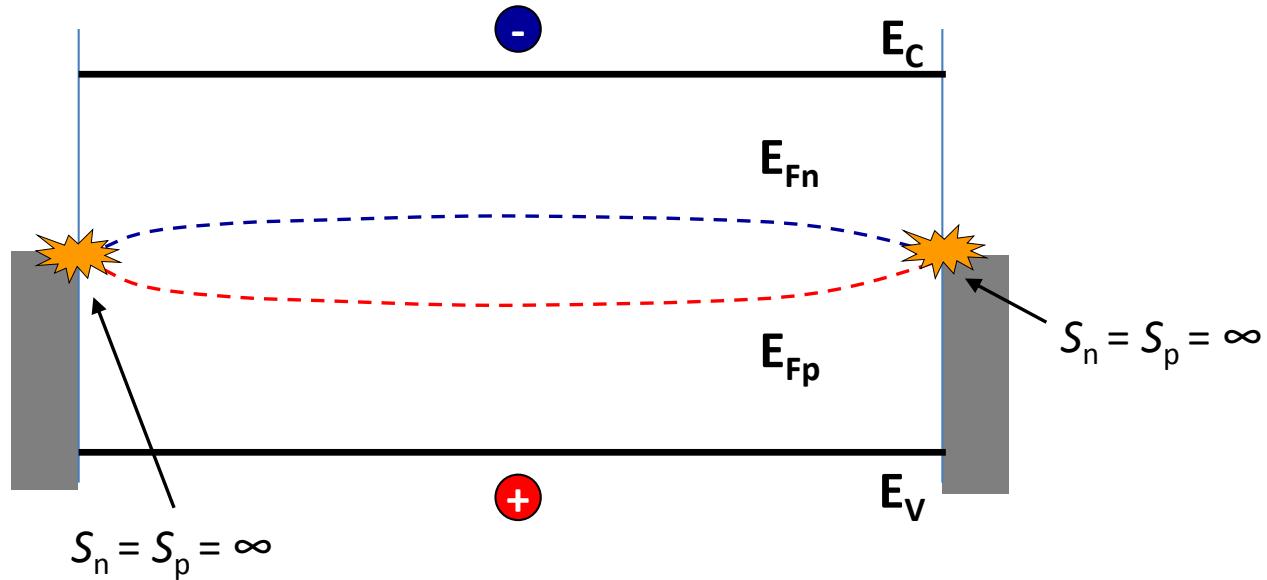


Surface recombination  
velocities  $S_n, S_p$ :

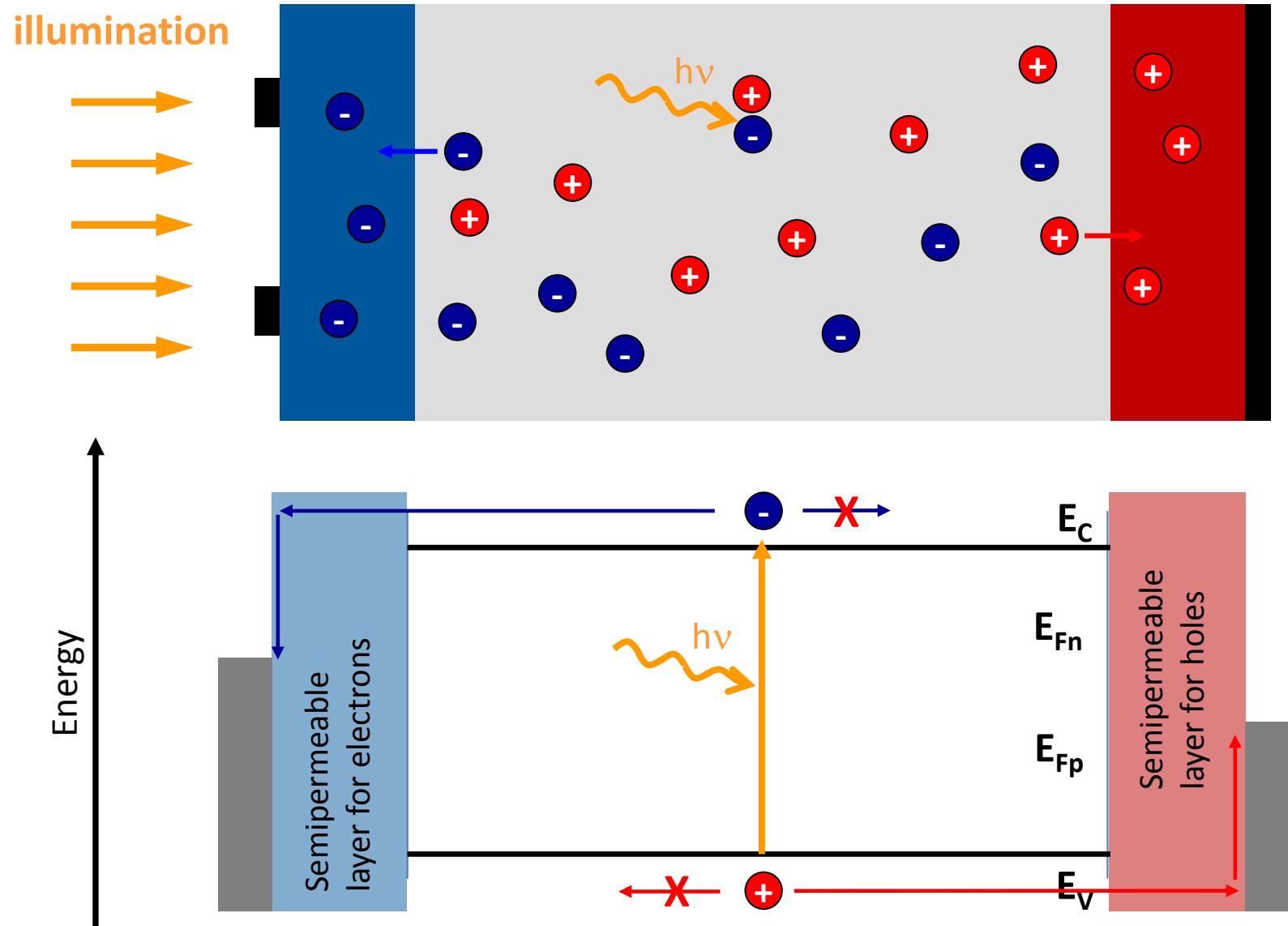
$$S_n = D_n \frac{dn}{dt} \Big|_s / (n - n_0)_s$$

$$S_p = D_p \frac{dp}{dt} \Big|_s / (p - p_0)_s$$

$$\underbrace{U_s}_{\Delta p_s}$$

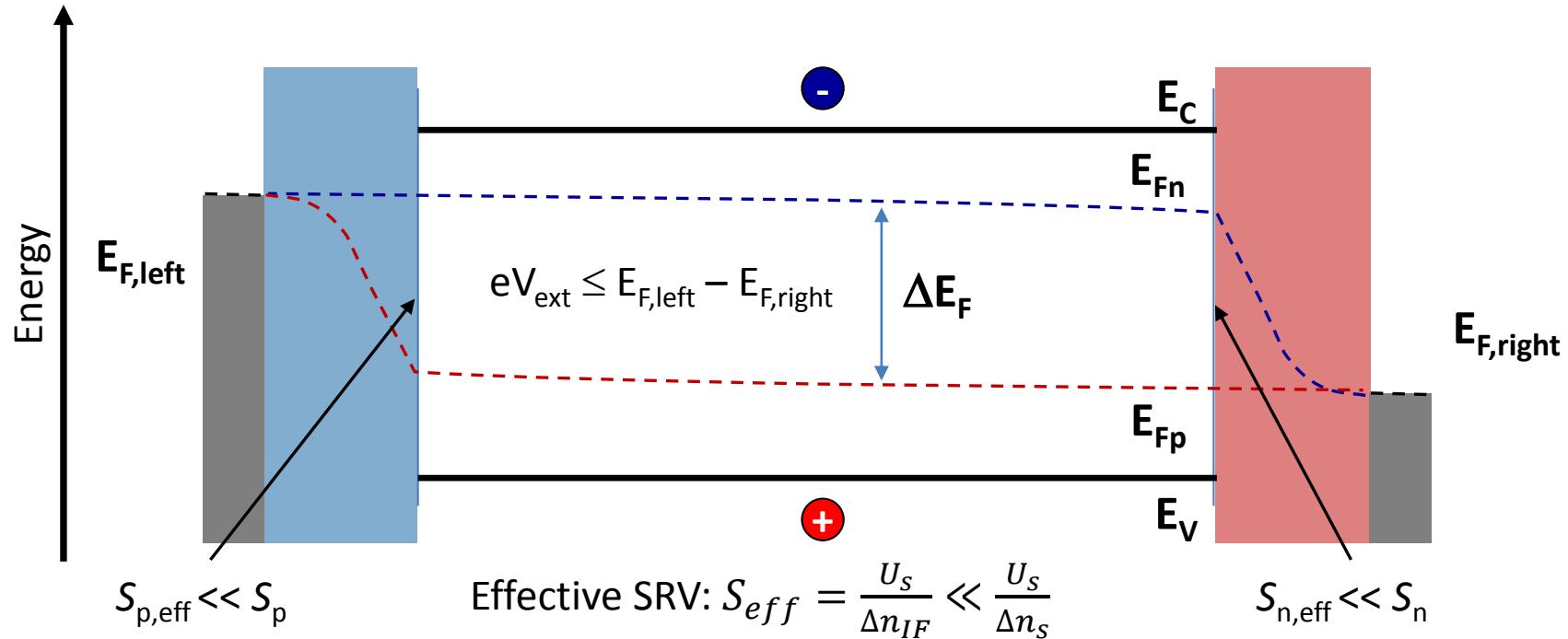
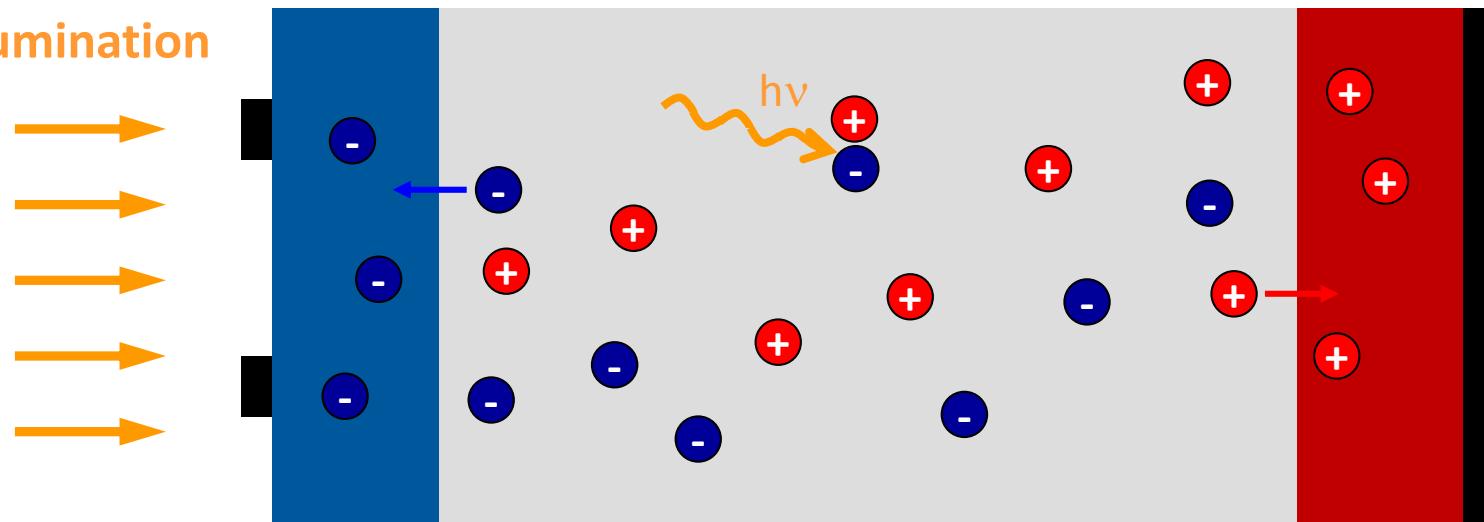


# Passivating carrier-selective contacts

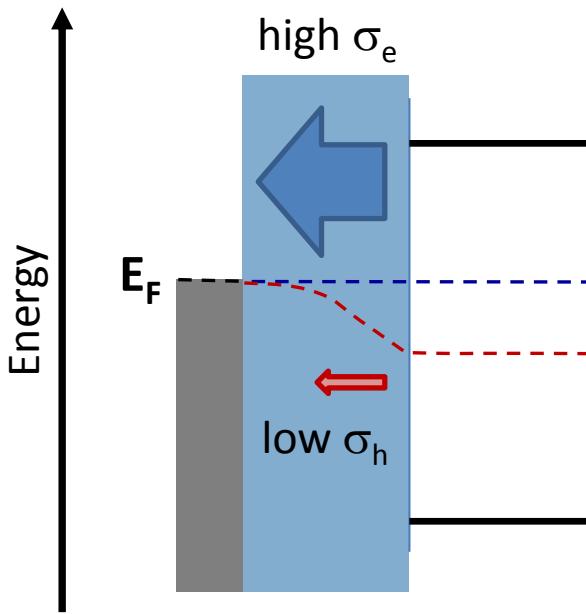


# Passivating carrier-selective contacts

illumination



# What are our options to achieve carrier selectivity?



**Charge current of electrons:**

$$j_e = \frac{\sigma_e}{e} \text{grad } E_{f,n}$$

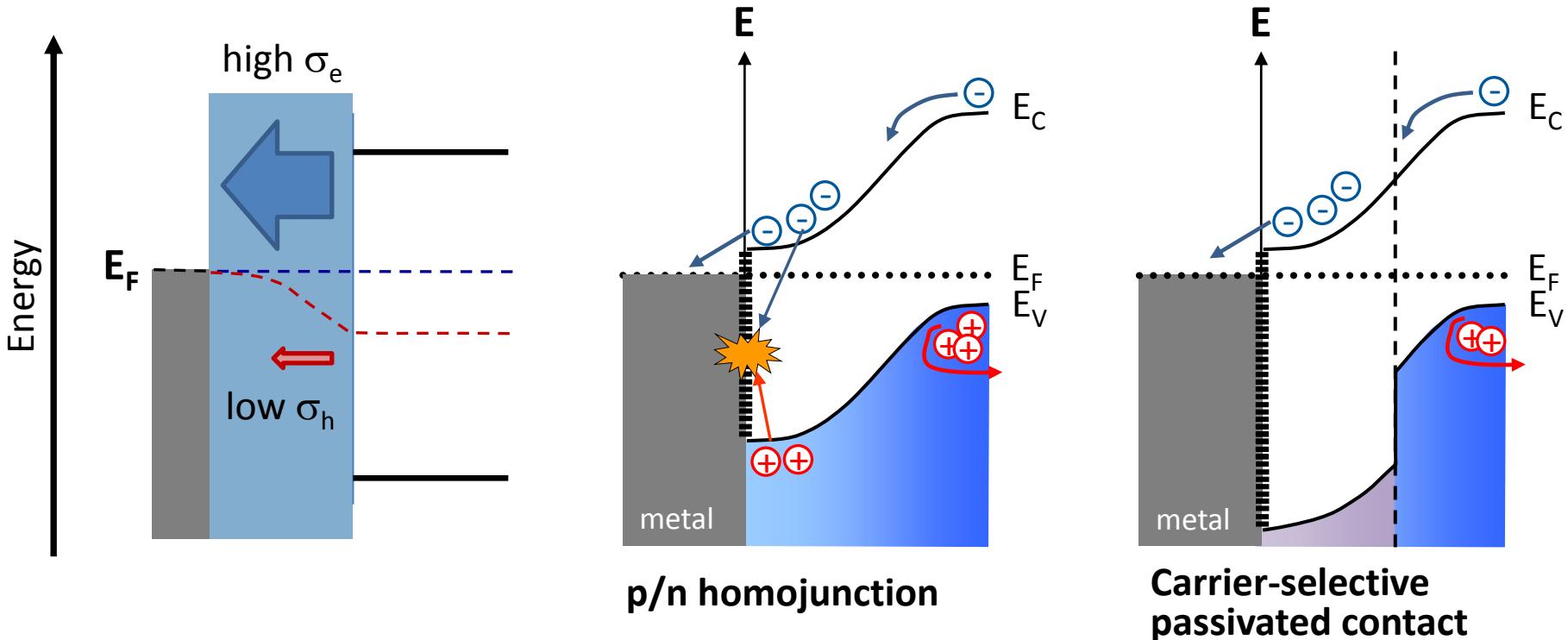
**Charge current of holes:**

$$j_h = \frac{\sigma_h}{e} \text{grad } E_{f,p}$$

→ Change current flow towards contact by *changing carrier type's conductivity*  $\sigma_i = \pm en_i\mu_i$  i.e., change

- **carrier concentration** ( $E_{Fp} - E_V, E_{Fn} - E_C$ )
  - **doping** → “classical” p/n junctions
  - **band offsets** → “novel” CSCs
- (carrier mobility  $\mu$ )

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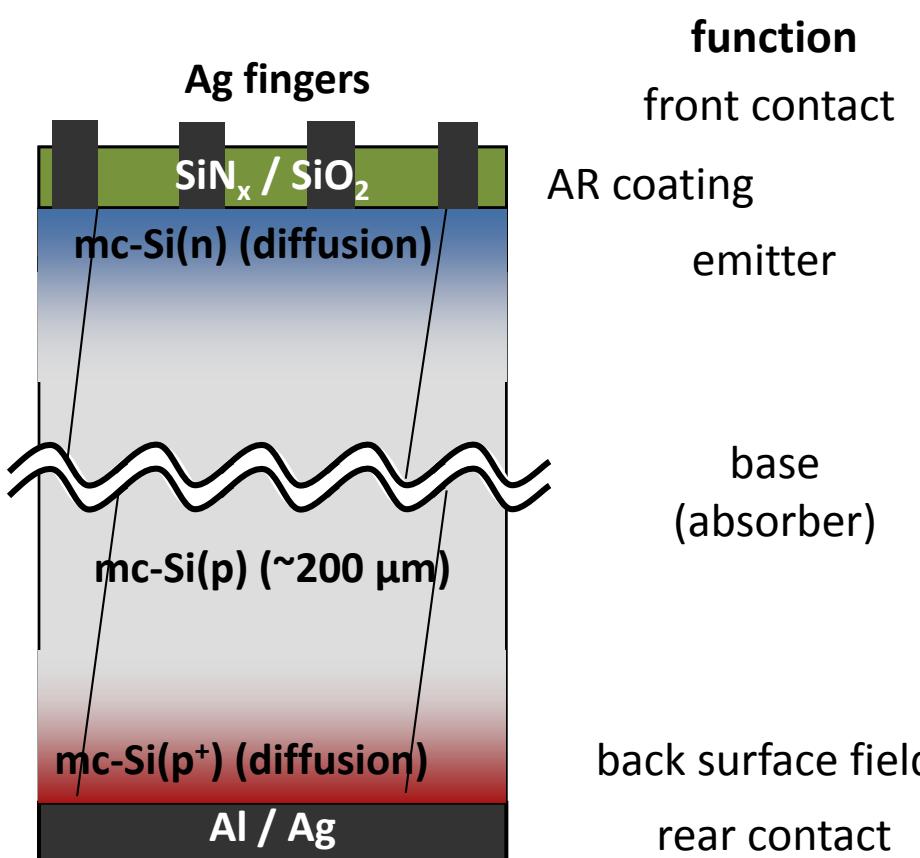
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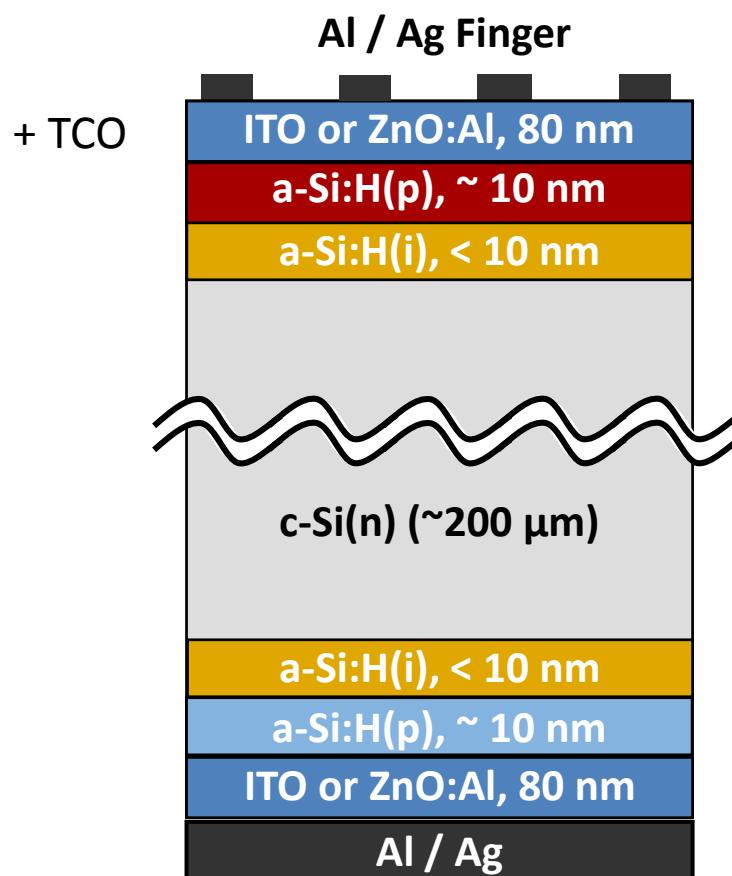
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  - (carrier mobility  $\mu$ )

# Silicon-homo- and heterojunction solar cells

## standard diffused junction

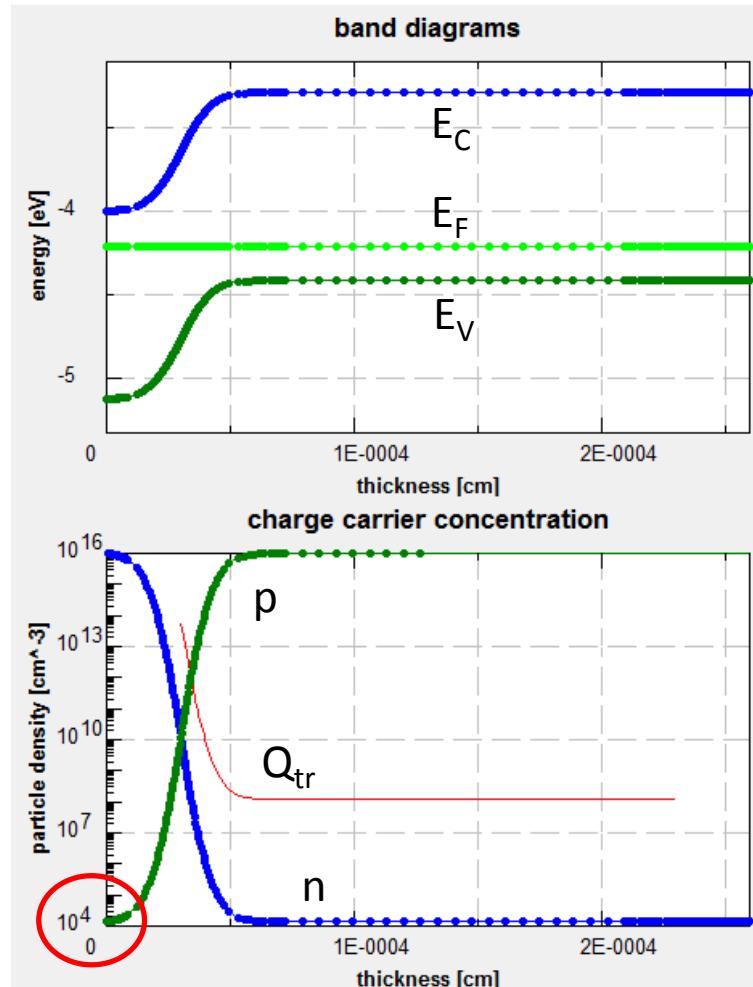


## a-Si:H/c-Si heterojunction the “prototypical” CSC cell...

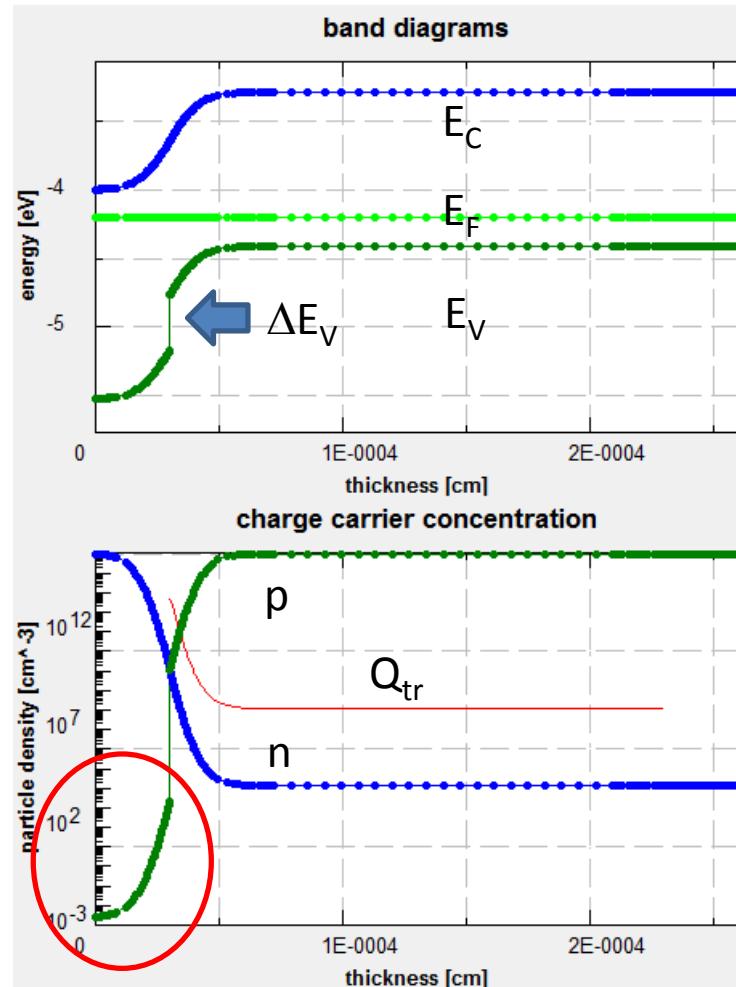


# p/n homo- vs. heterojunction

in the dark,  $V_{\text{ext}} = 0$   
homojunction



heterojunction

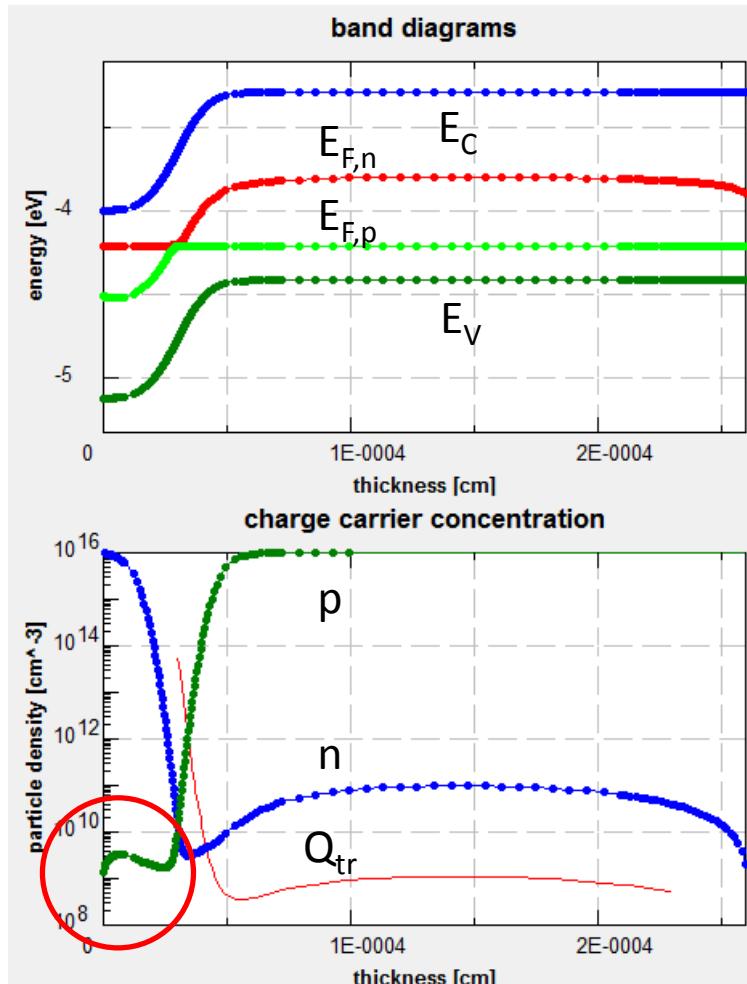


Heterojunction:  $10^7$  times lower hole density at (n) contact → improved carrier selectivity?

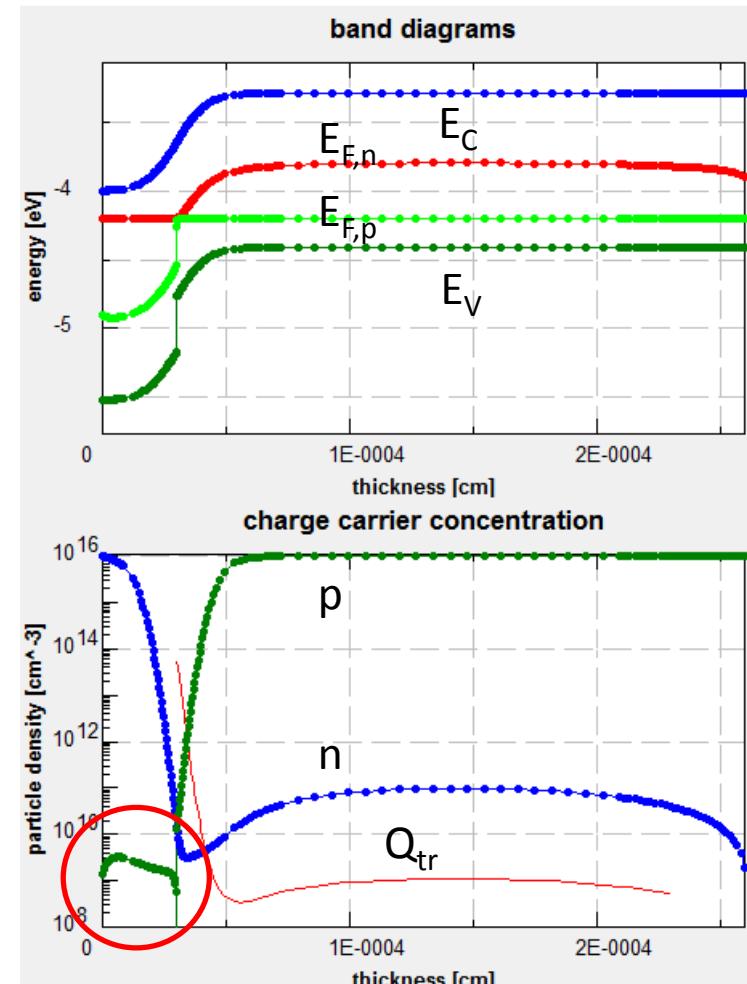
# p/n homo- vs. heterojunction

AM1.5 illumination,  $V_{\text{ext}} = 0$

homojunction



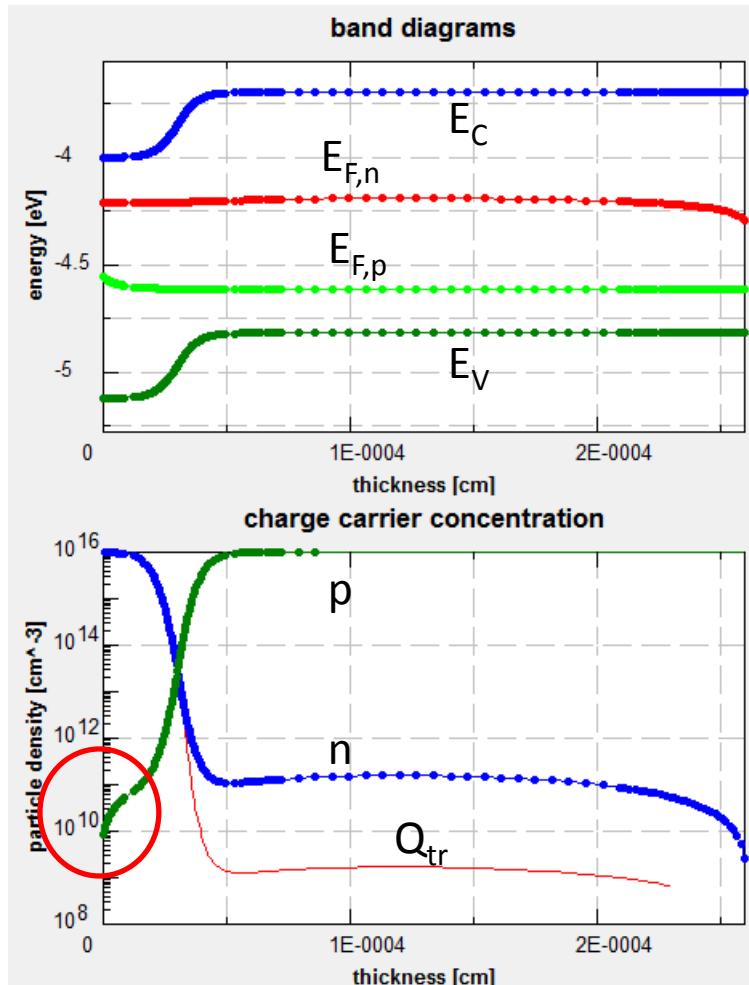
heterojunction



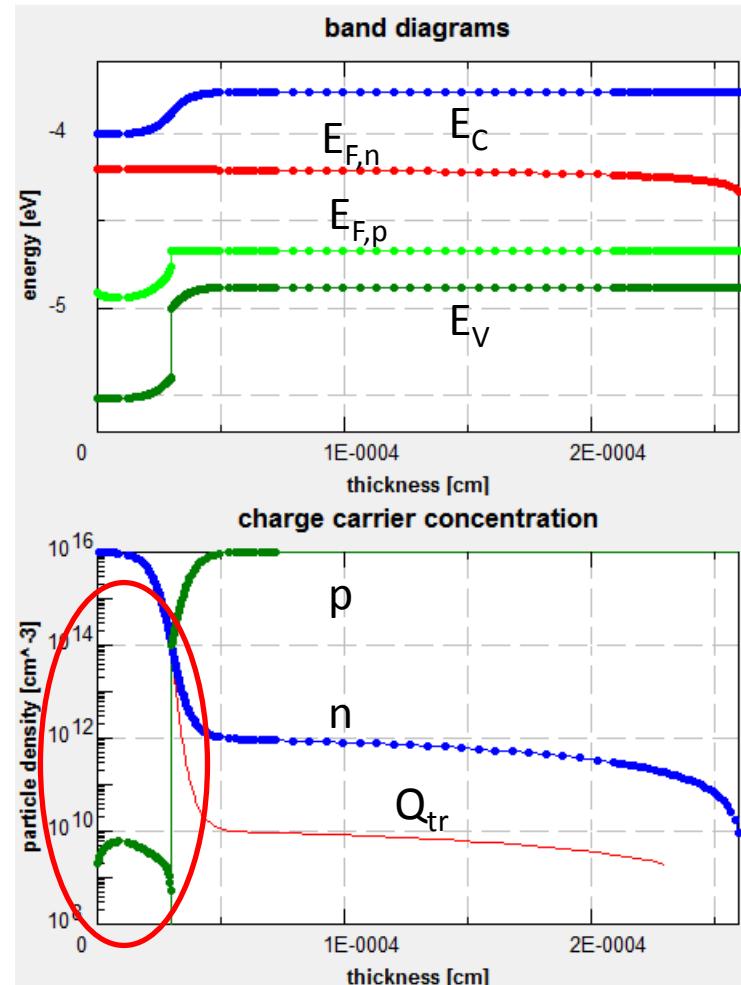
Illuminated, at  $j_{\text{sc}}$ : p @ junction strongly increased, but still lower in HET

# p/n homo- vs. heterojunction

AM1.5 illumination,  $V_{\text{ext}} = V_{\text{oc}}$   
homojunction

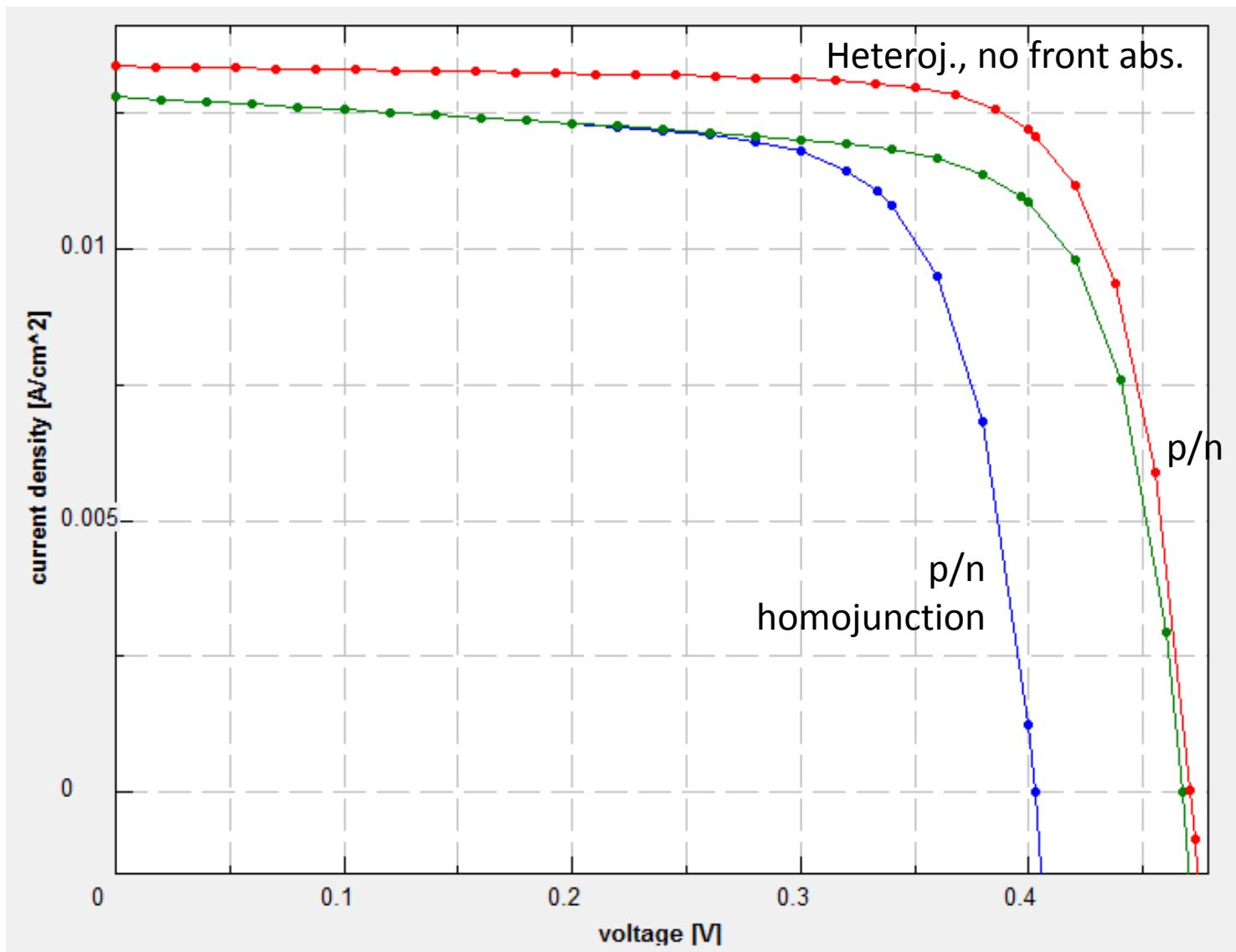


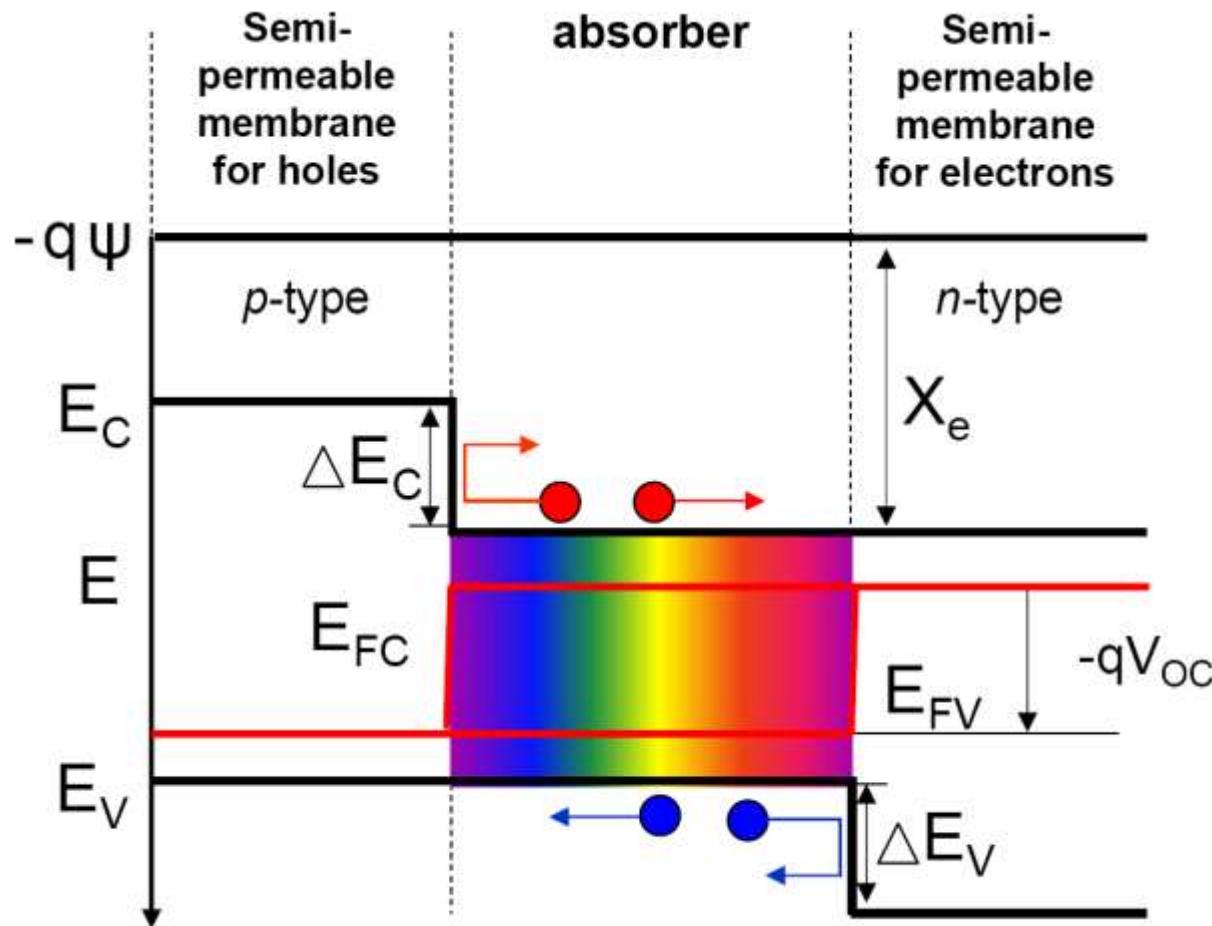
**heterojunction**



Illuminated, at  $V_{\text{oc}}$ : p “left of” heterointerface  $\sim 10^5$  times lower than in homojunction!

# Comparison of simulated I-V curves



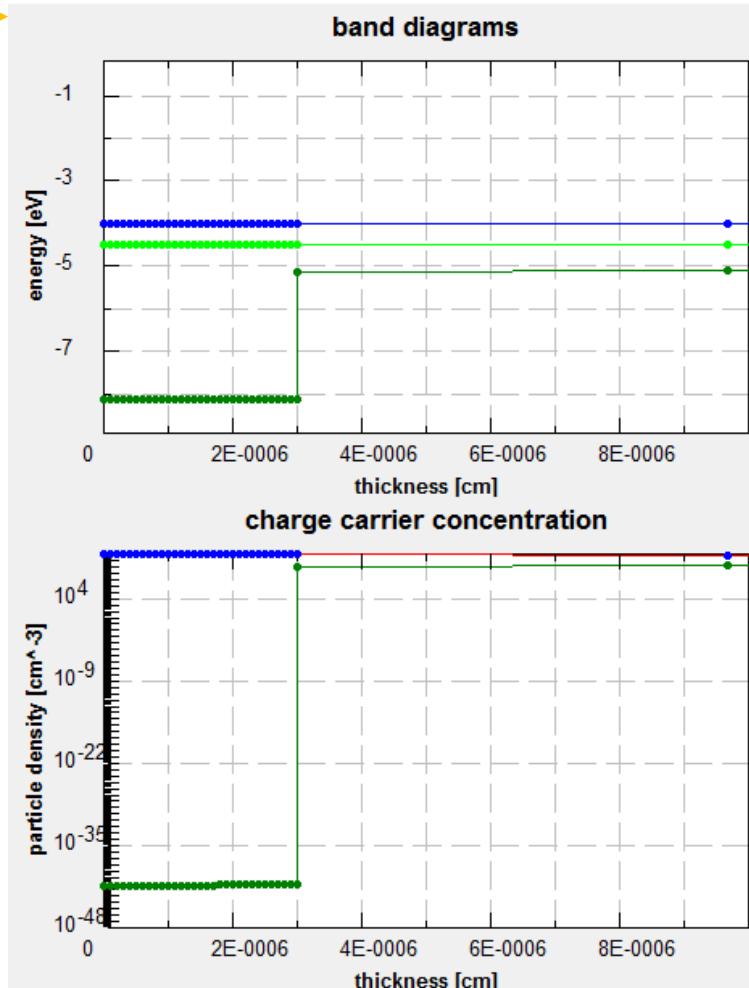
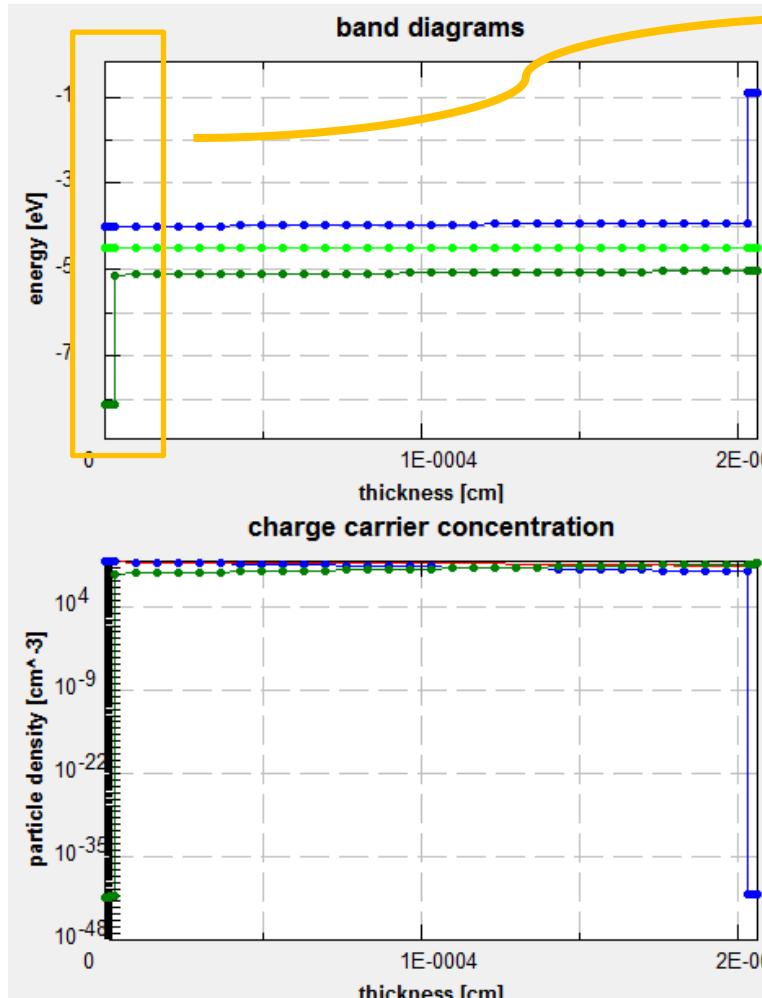


source: Zeman, Zhang, in: van Sark/Korte/Roca:  
Physics and Tech. of aSi/cSi Heterostructure cells

# (almost) ideal carrier-selective contacts

(c-Si,  $\Delta E_{V,front} = \Delta E_{C,rear} = 3\text{eV}$ ,  $N_A, N_D = 10^{11}/\text{cm}^3$ , 2 $\mu\text{m}$  absorber, 30nm contacts)

in the dark,  $V_{ext} = 0$

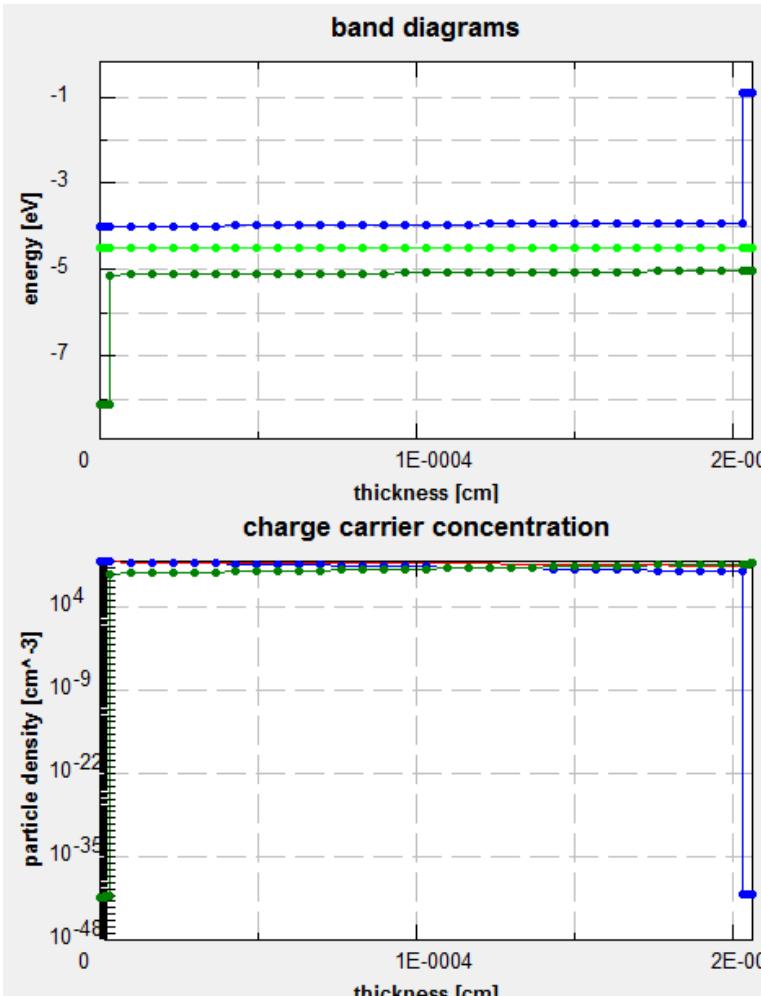


Very high carrier selectivity:  $(n_s/p_s)_{Front} = (p_s/n_s)_{Back} > 10^{50}$

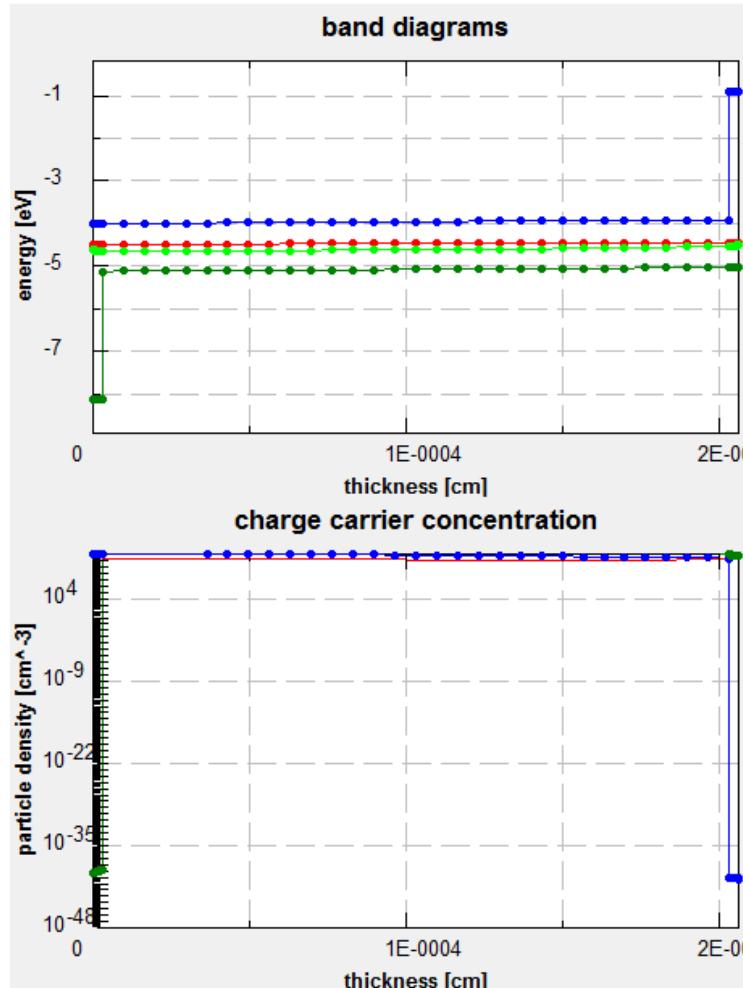
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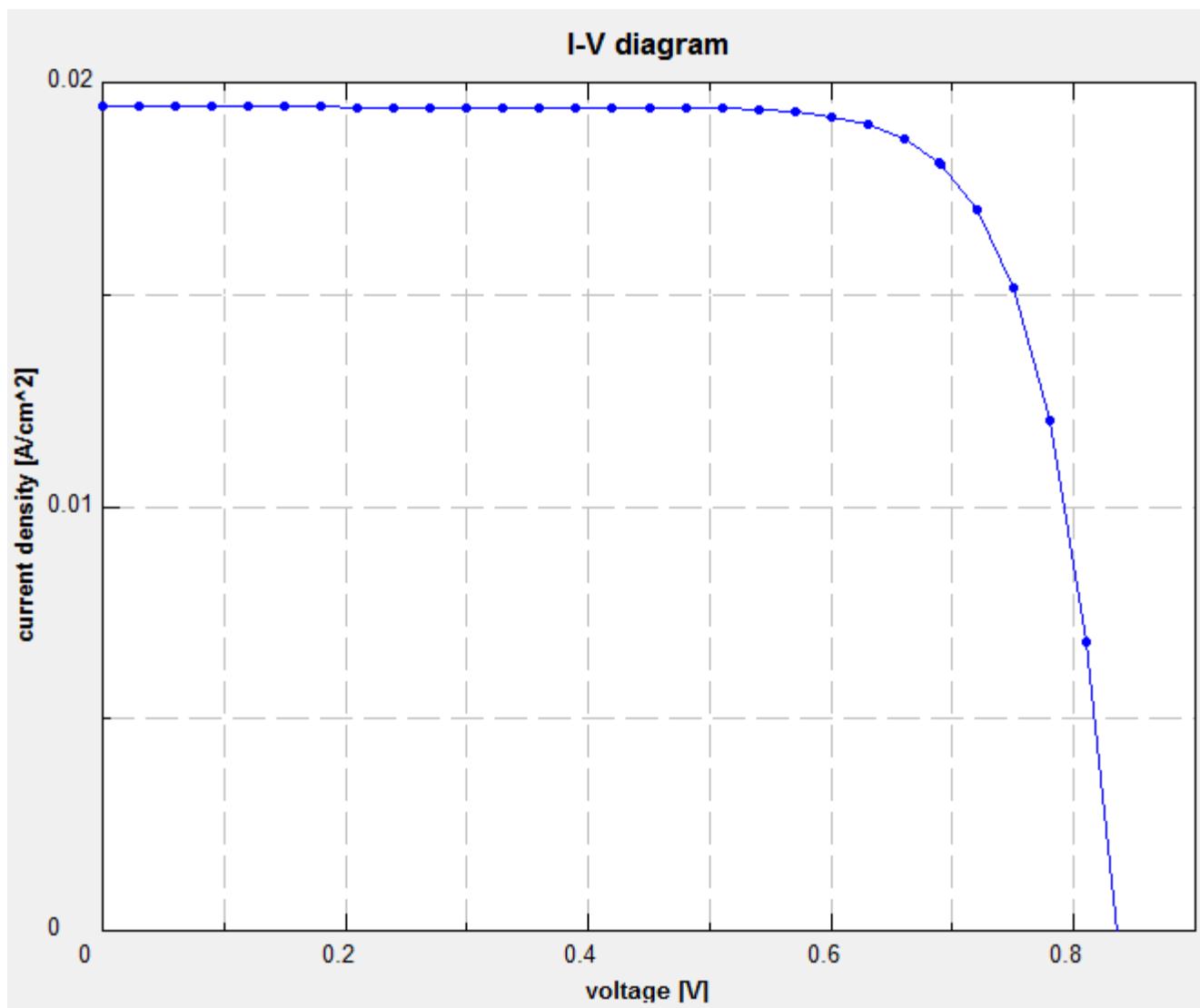


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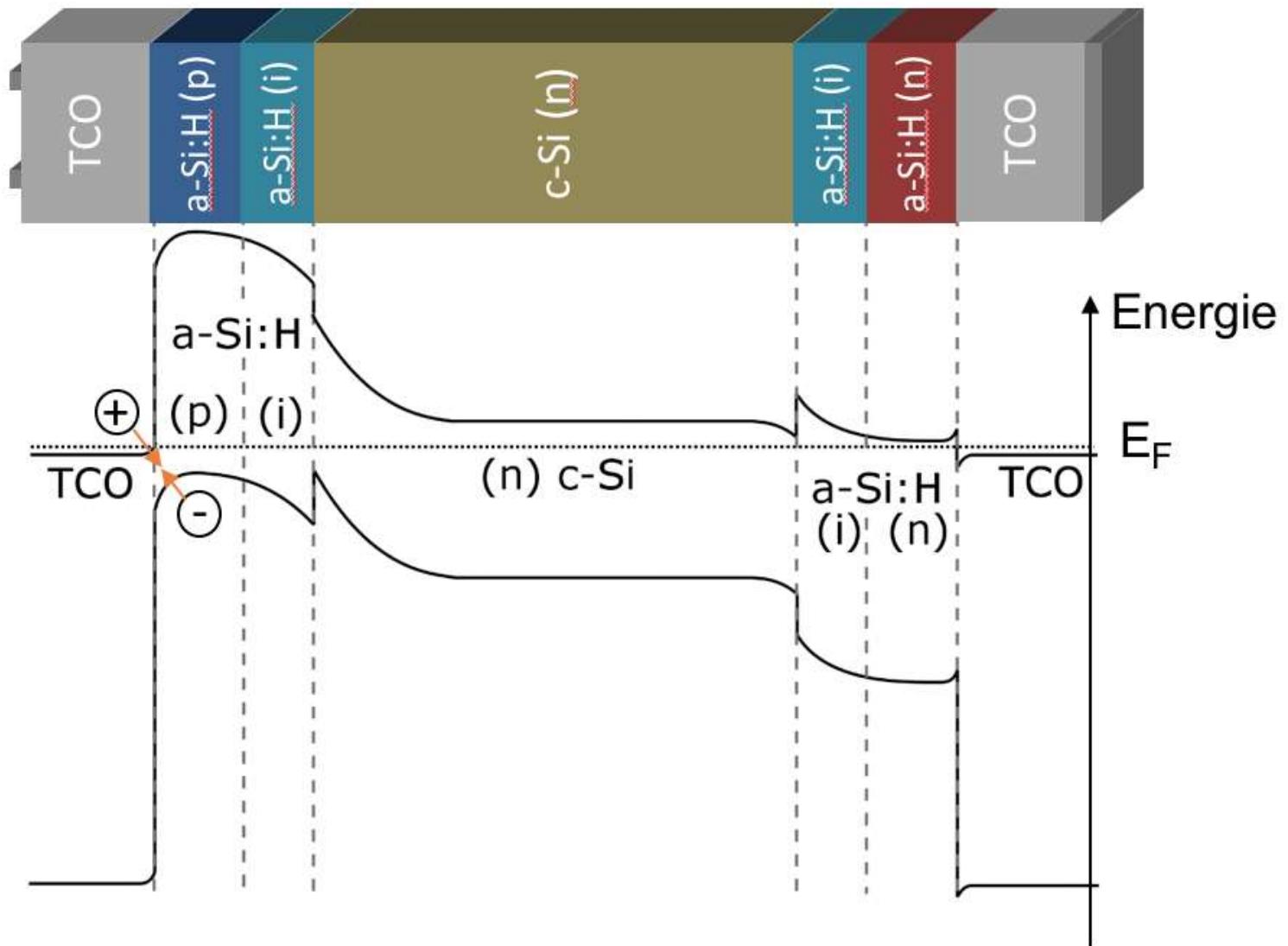
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# (almost) ideal carrier-selective contacts

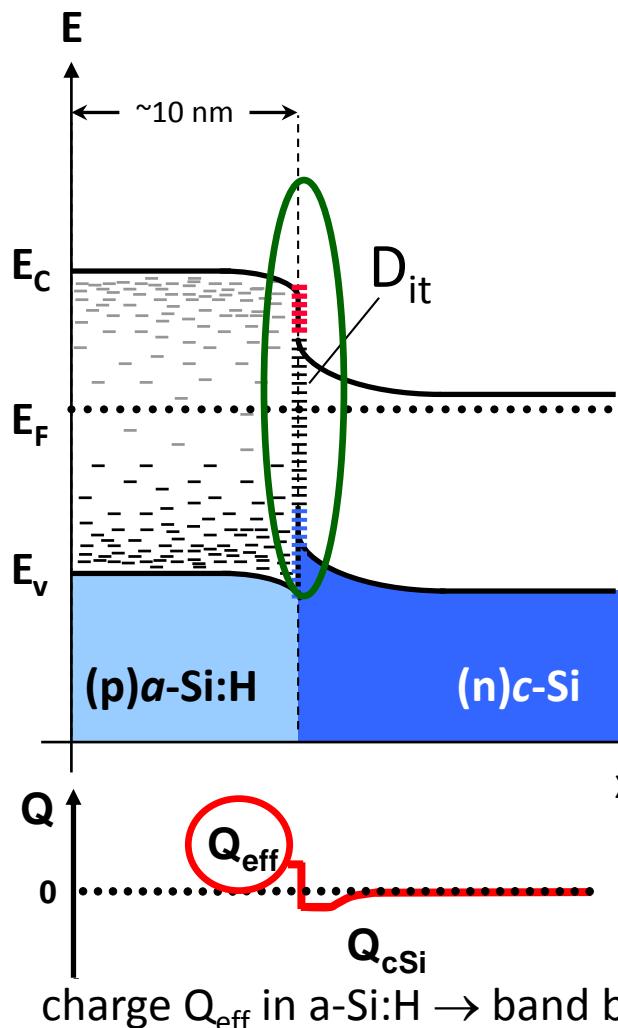


V<sub>oc</sub> = 836mV, FF = 76.7%, j<sub>sc</sub> = 19.4mA/cm<sup>2</sup> (only 2μm c-Si absorber!)

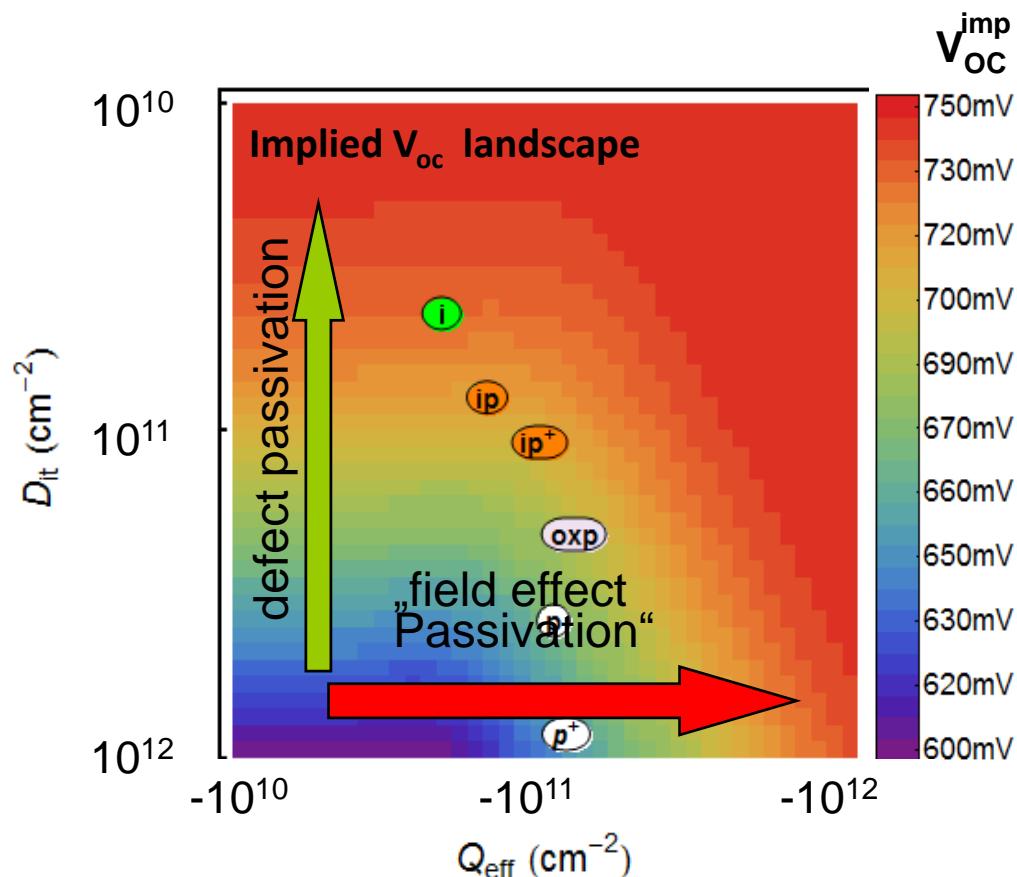
# Amorphous/crystalline silicon heterojunction solar cell



# influence of interface defects and fixed charge on cell $V_{oc}$ - simulation study



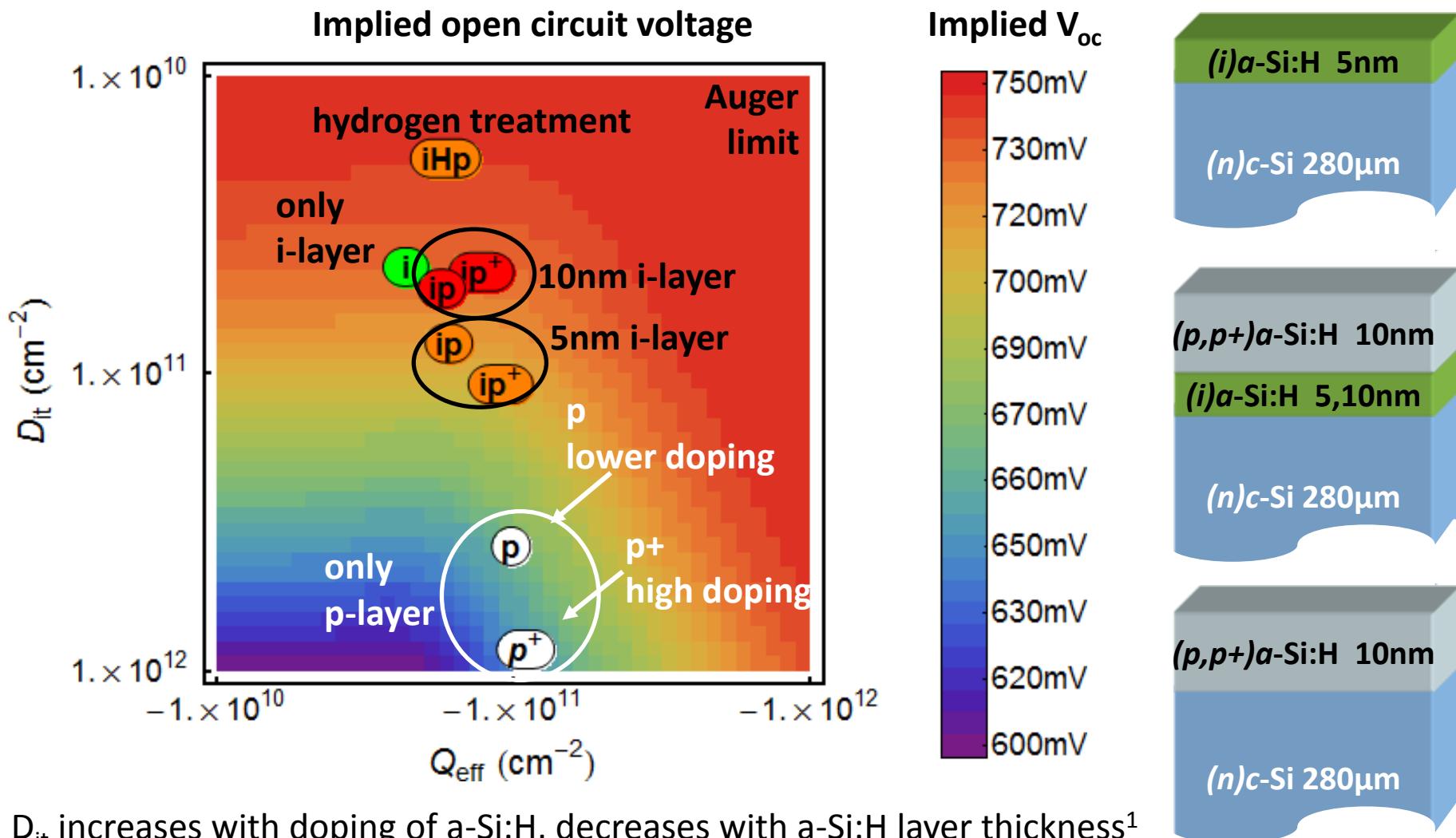
ElFanT : semianalytical MATLAB model



charge  $Q_{eff}$  in a-Si:H  $\rightarrow$  band bending

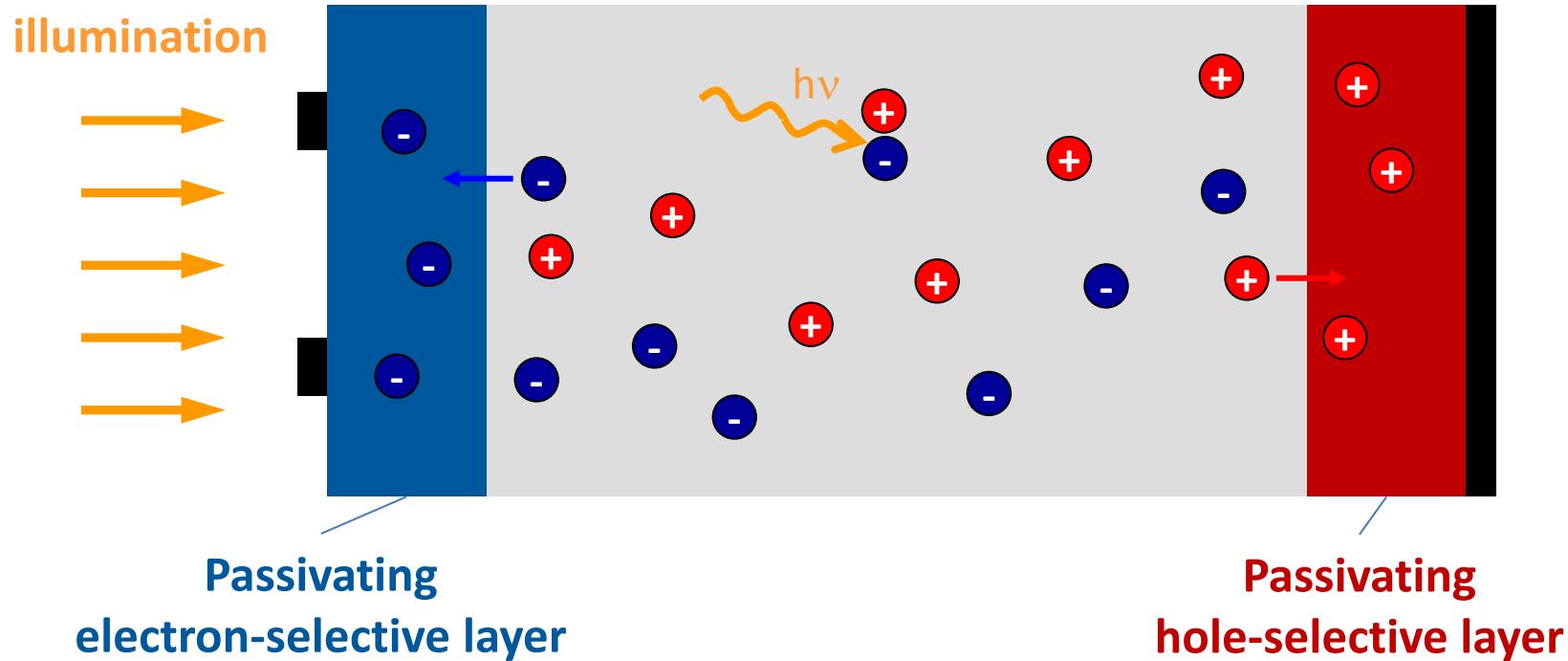
- strong influence of interface recombination at front (and rear) side
- $D_{it} < 10^{10} \text{ cm}^{-2} \rightarrow \text{IF recombination plays no role in cell}$

# Impact of i/p stack parameters on implied $V_{oc}$



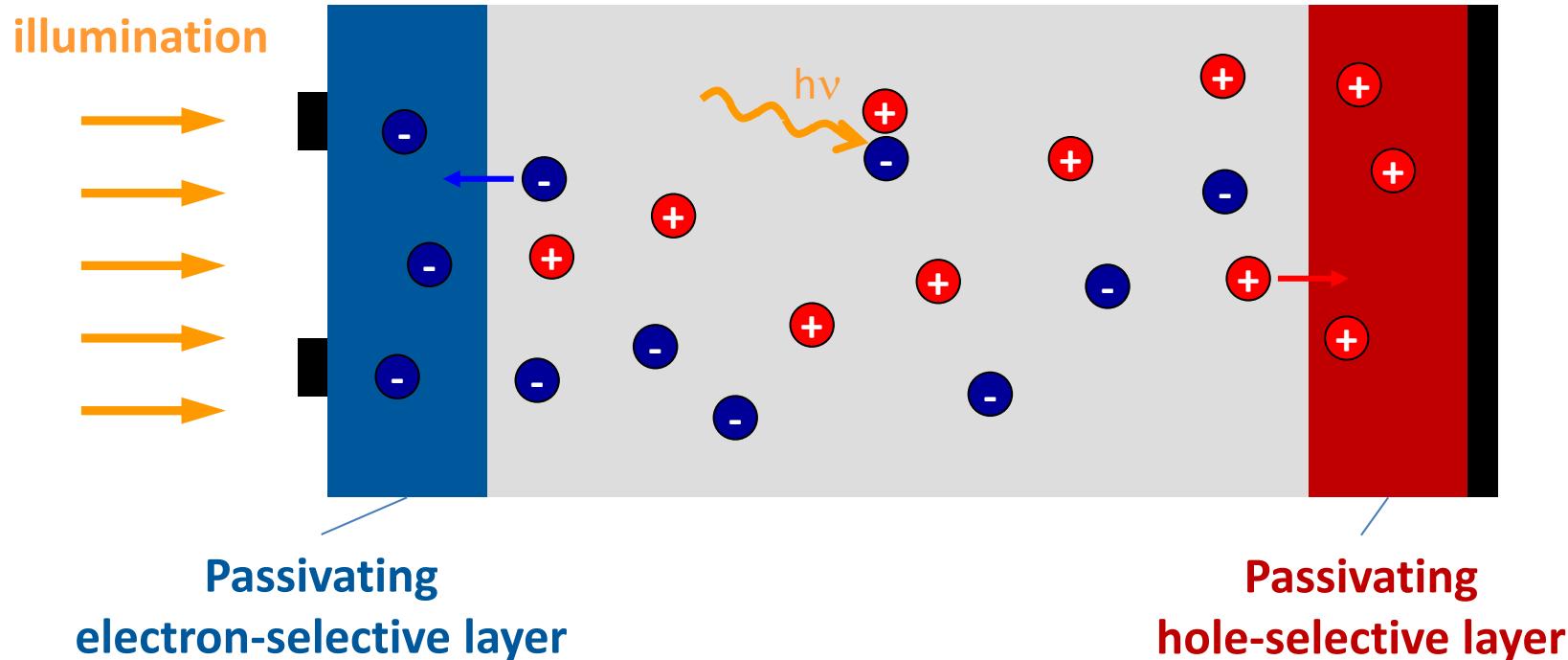
- $D_{it}$  increases with doping of a-Si:H, decreases with a-Si:H layer thickness<sup>1</sup>
- $V_{oc}$  is mainly governed by  $D_{it}$ ;  $Q_{\text{eff}}$  has minor influence
- State of the art layers stacks close to the Auger limit

<sup>1</sup>S. de Wolf & M. Kondo, J. Appl. Phys., **105**, (2009)



## Key parameters of Carrier Selective Contacts

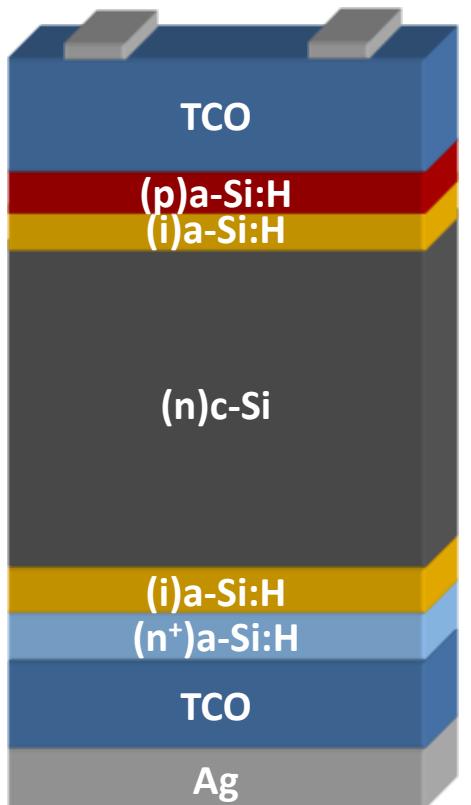
- Suitable energy band alignment
- Passivation (or non-existence) of interface defects
- Optical transparency
- (high electronic conductivity)



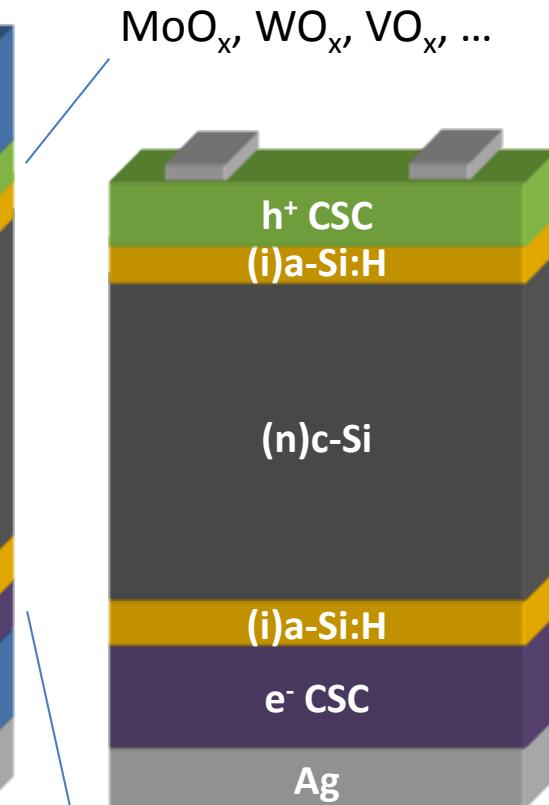
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# Carrier selective contacts for c-Si solar cells

“classical” a-Si:H/c-Si  
heterojunction solar cell



CSC- based solar cells



MoO<sub>x</sub>, WO<sub>x</sub>, VO<sub>x</sub>, ...

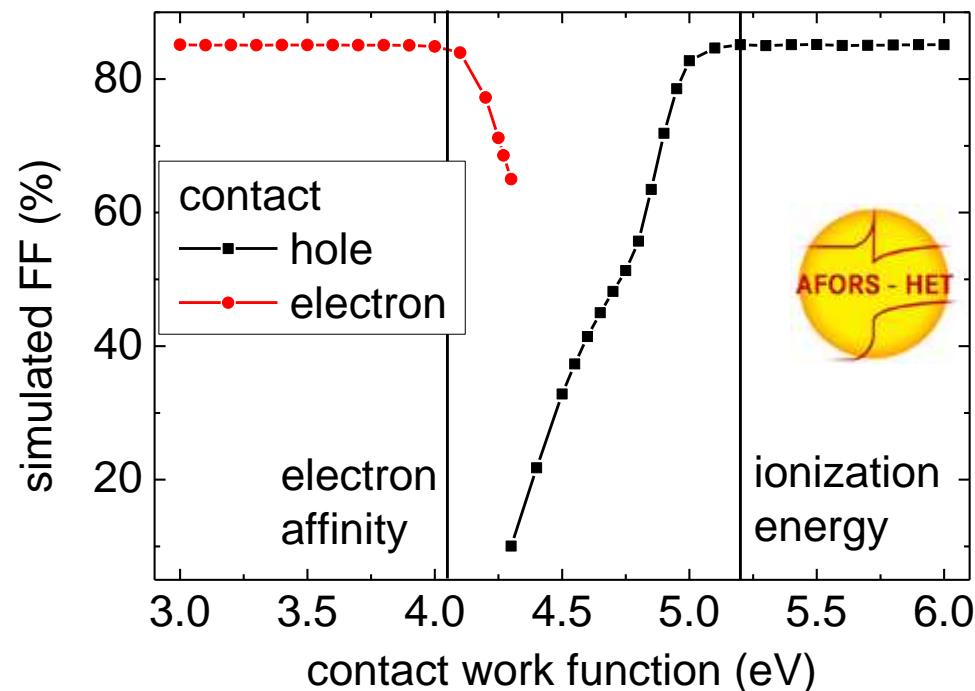
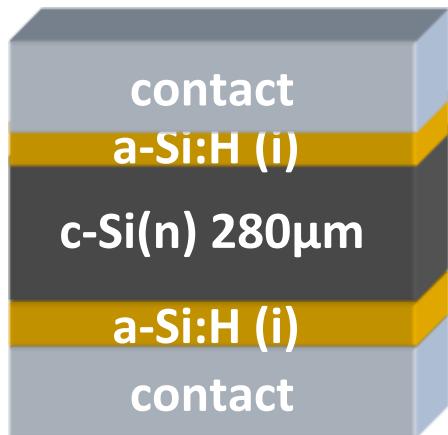
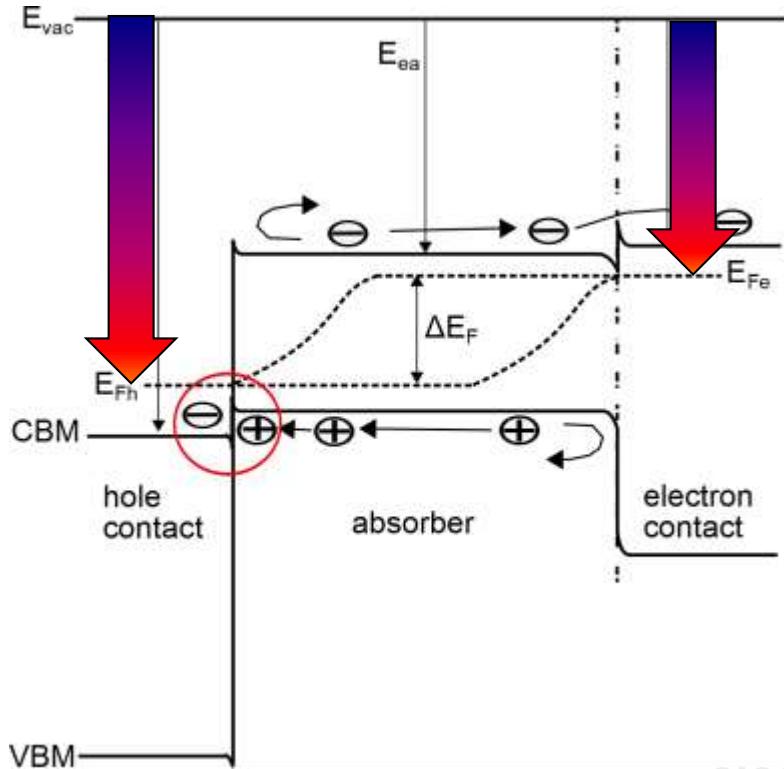


TiO<sub>2</sub>, MgF<sub>2</sub>, ...

Replace doped layers by “carrier selective” layers

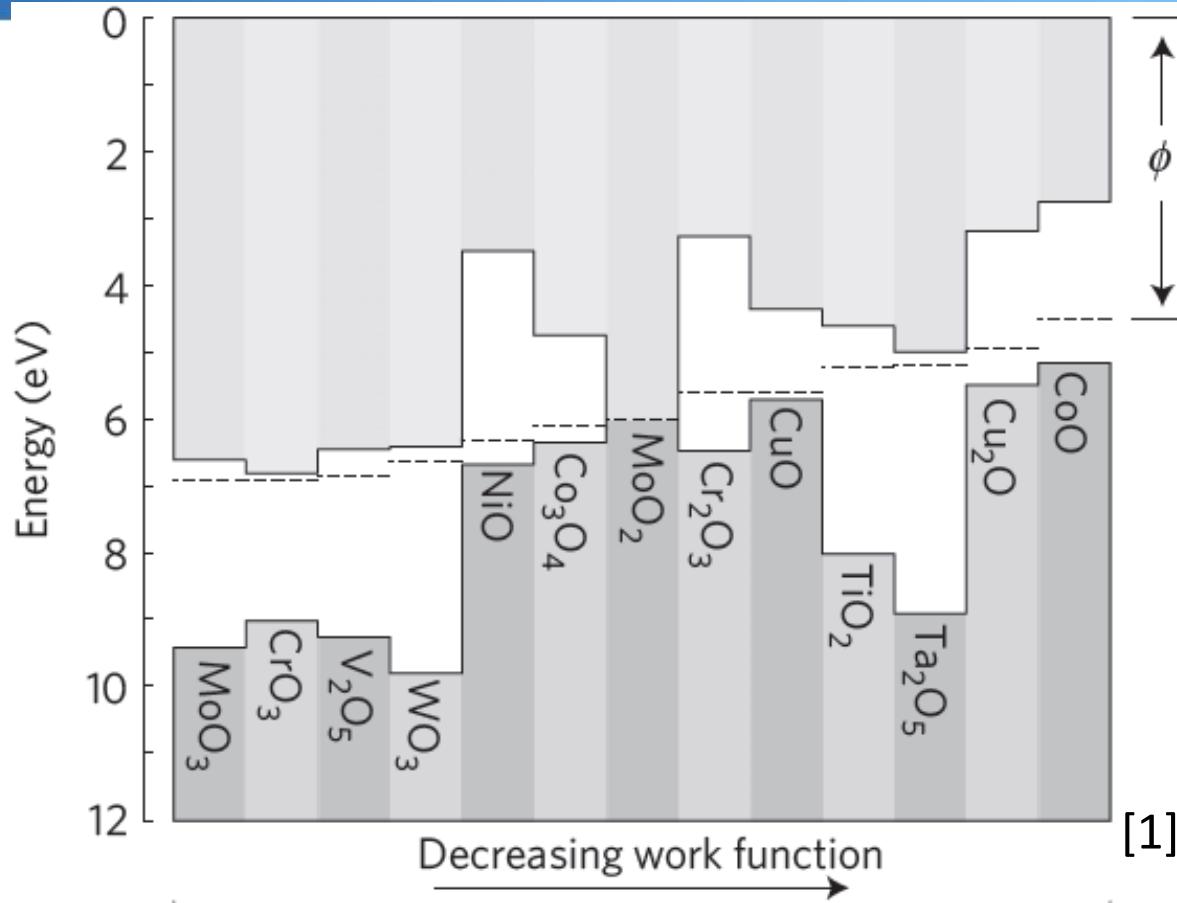
- Highly transparent front contact
- Might also replace TCOs if sheet resistivity is low enough (front), optics OK
- Even omit passivating layers (a-Si:H, SiO<sub>2</sub>)?

# Work functions for selective contacts on Si



- **electron contact: work function  $\phi_{ETM} < \phi_{cSi}$**   
in (n)cSi with  $e^-$  accumulation up to degeneration:  
 $\phi_{cSi}$  = electron affinity  $\chi_{cSi}$        $\rightarrow \phi_{ETM} < \chi_{cSi}$
- **hole contact: work function  $\phi_{HTM} > \phi_{cSi}$**   
in (n)cSi with  $h^+$  inversion layer up to degeneration:  
 $\phi_{cSi}$  = ionization potential  $I^*_{cSi}$        $\rightarrow \phi_{HTM} > I^*_{cSi}$

# High work function contact materials



- organic photovoltaic community → MoO<sub>x</sub>, WO<sub>x</sub>, V<sub>2</sub>O<sub>5</sub> [1]
- SHJ/c-Si solar cells with MoO<sub>x</sub> [2,3], WO<sub>x</sub> [4], V<sub>2</sub>O<sub>5</sub> [5]

[1] M. T. Greiner et al., Nature Mater. 11 (2012) 76-81

[2] C. Battaglia et al. Nano Lett. 14 (2014) 967-71 & Appl. Phys. Lett. 104 (2014) 113902

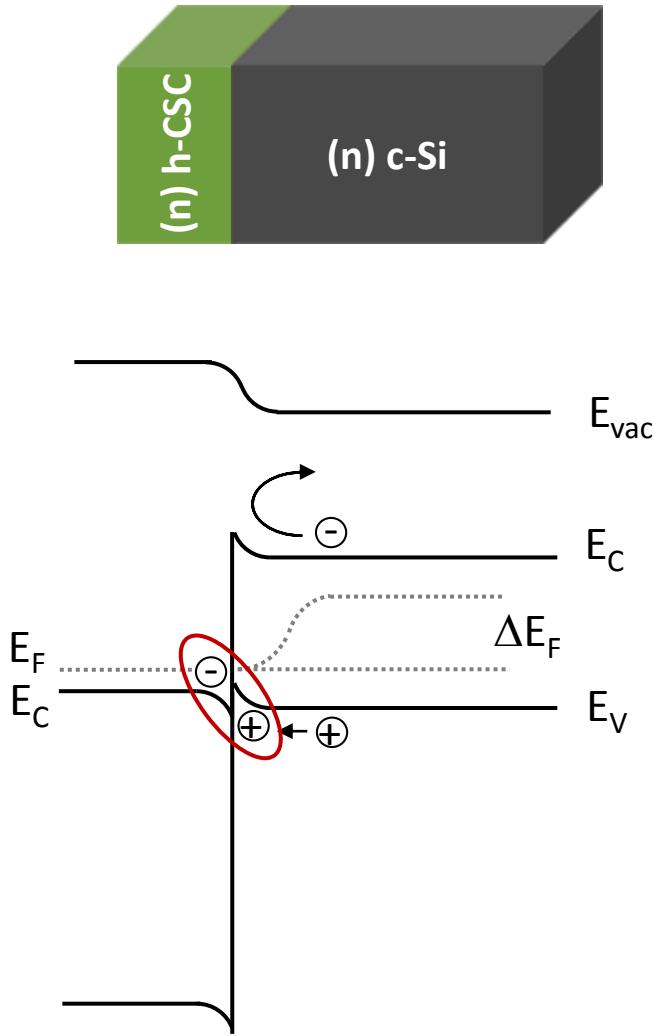
[3] J. Geissbühler et al. Appl. Phys. Lett. 107 (2015) 081601

[4] M. Bivour et al. Sol. En. Mat. Sol. Cells 142 (2015) 34-41

[5] L. G. Gerling et al. Sol. En. Mat. Sol. Cells 145 (2016) 109-15

# Carrier selective tunnel-recombination hole contact

→ Compare to the TCO/(p)a-Si:H contact in SHJ

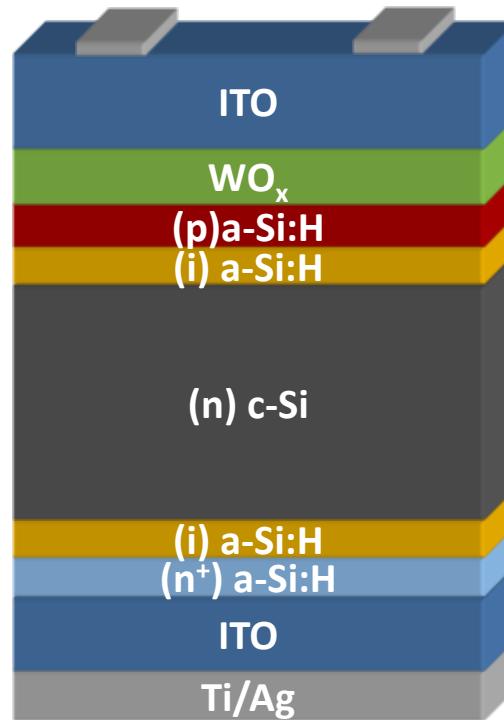
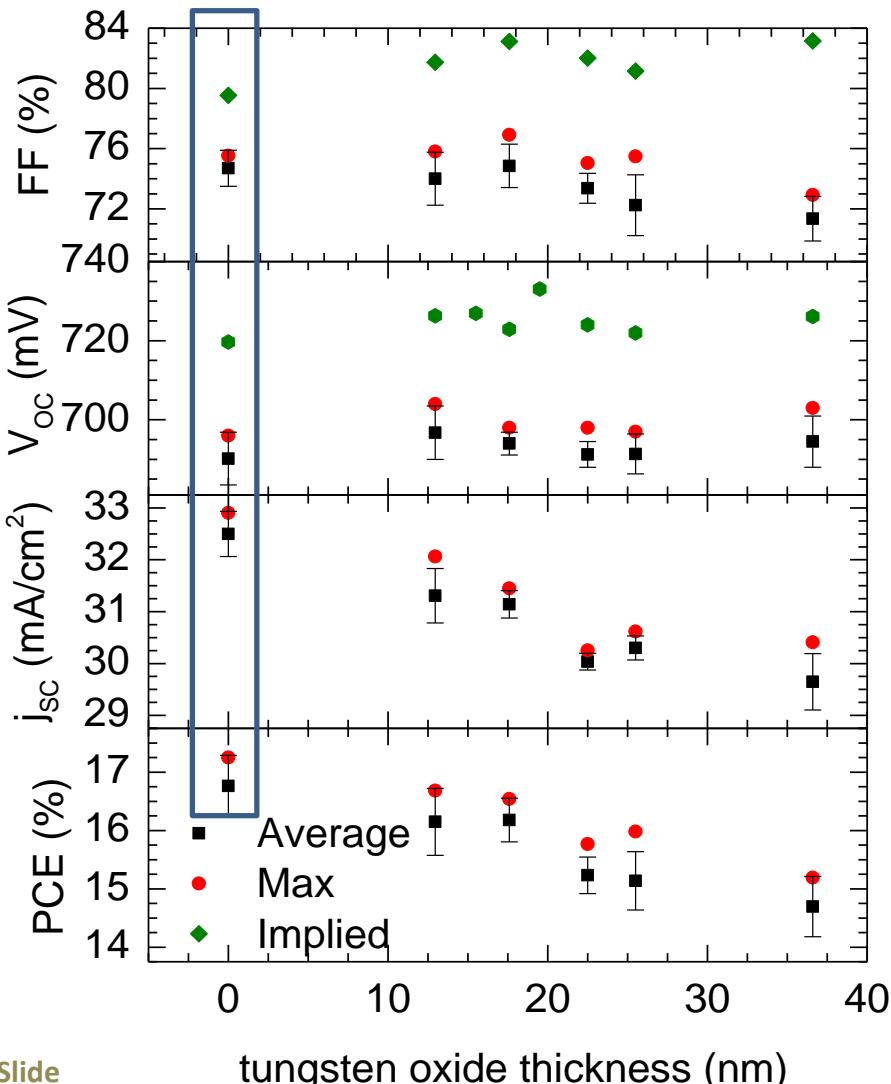


## WO<sub>x</sub>:

- n-type, high work function
- High stability (→ electrochromics, catalysis)

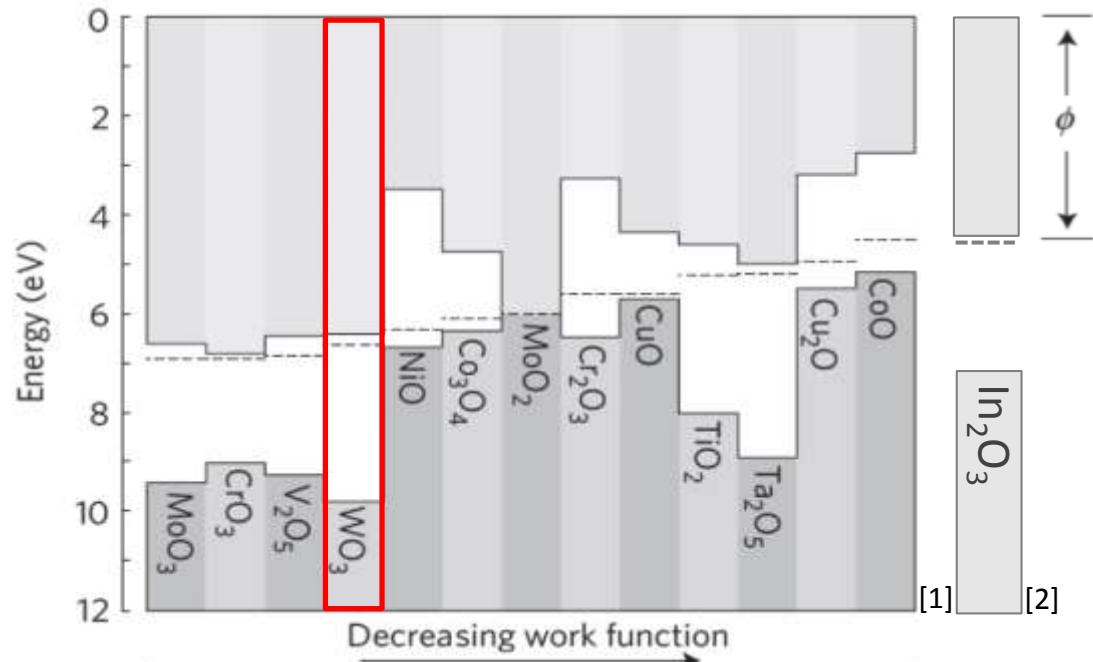
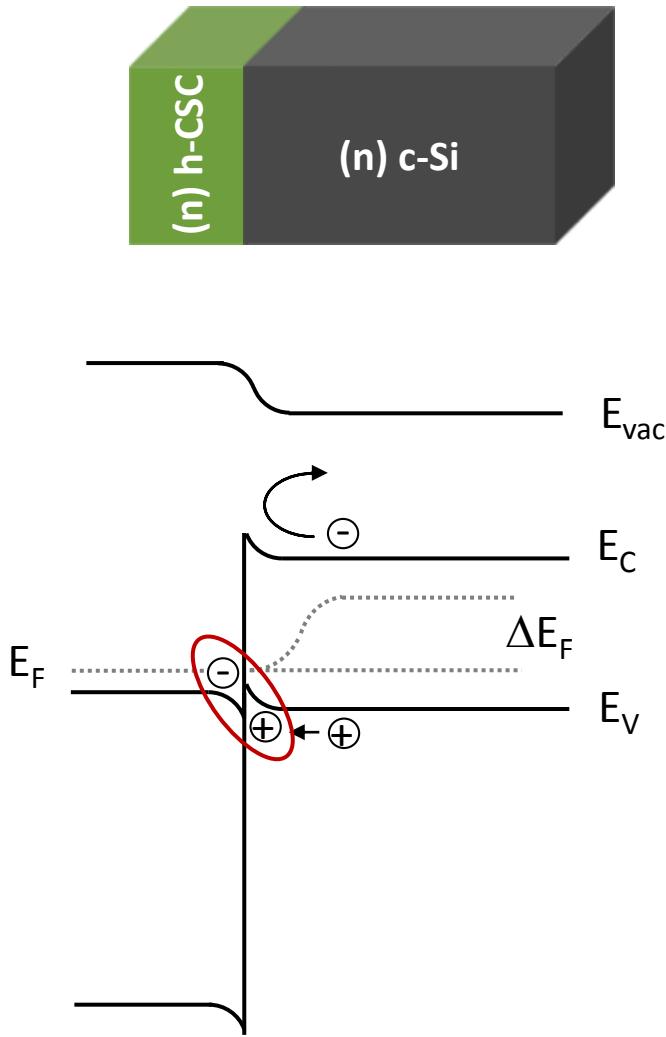
## WO<sub>x</sub> thickness variation and solar cells

(p,i)a-Si:H (ref.)



- Cells w/ WO<sub>x</sub>: FF limited by series resistance
- Best FF at 20 nm tungsten oxide

## Carrier selective tunnel-recombination hole contact

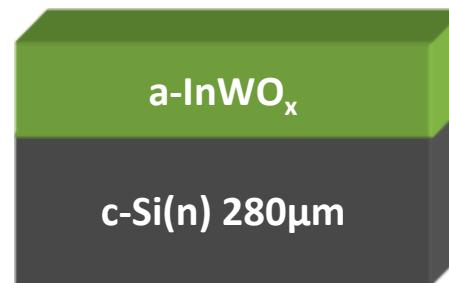
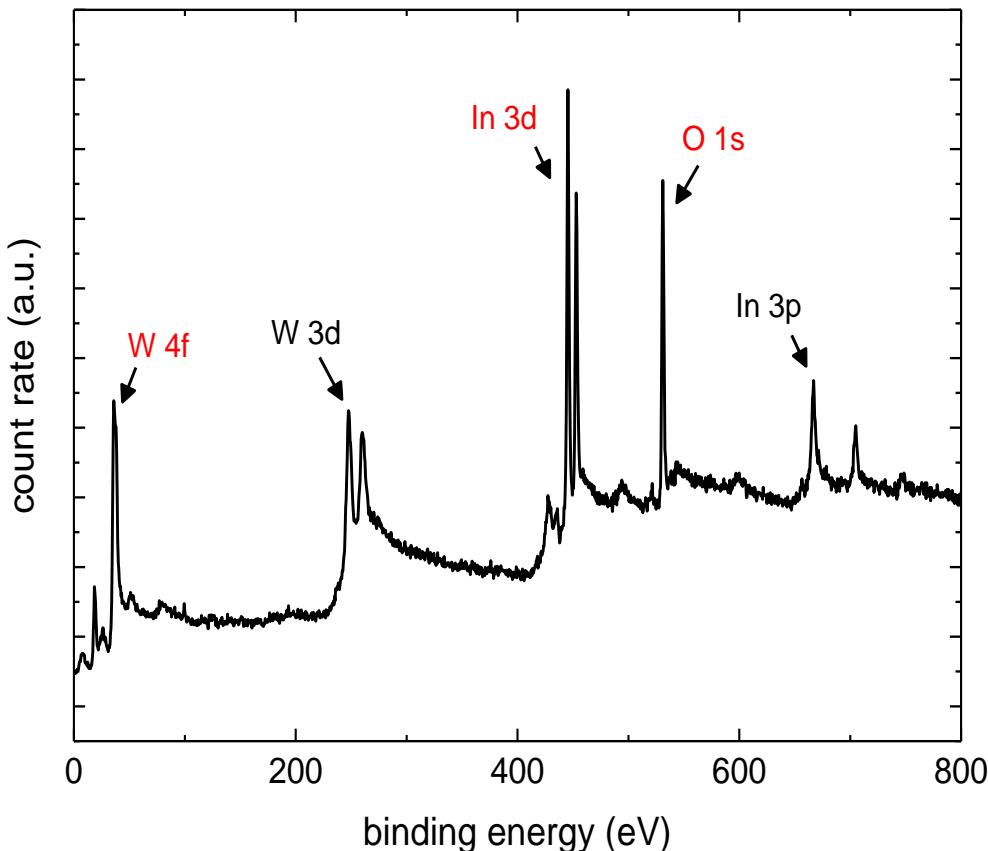


	WO <sub>3</sub>	In <sub>2</sub> O <sub>3</sub>
High work function	✓	✗
High conductivity	✗	✓

→ Find trade-off in indium tungsten oxide alloy?

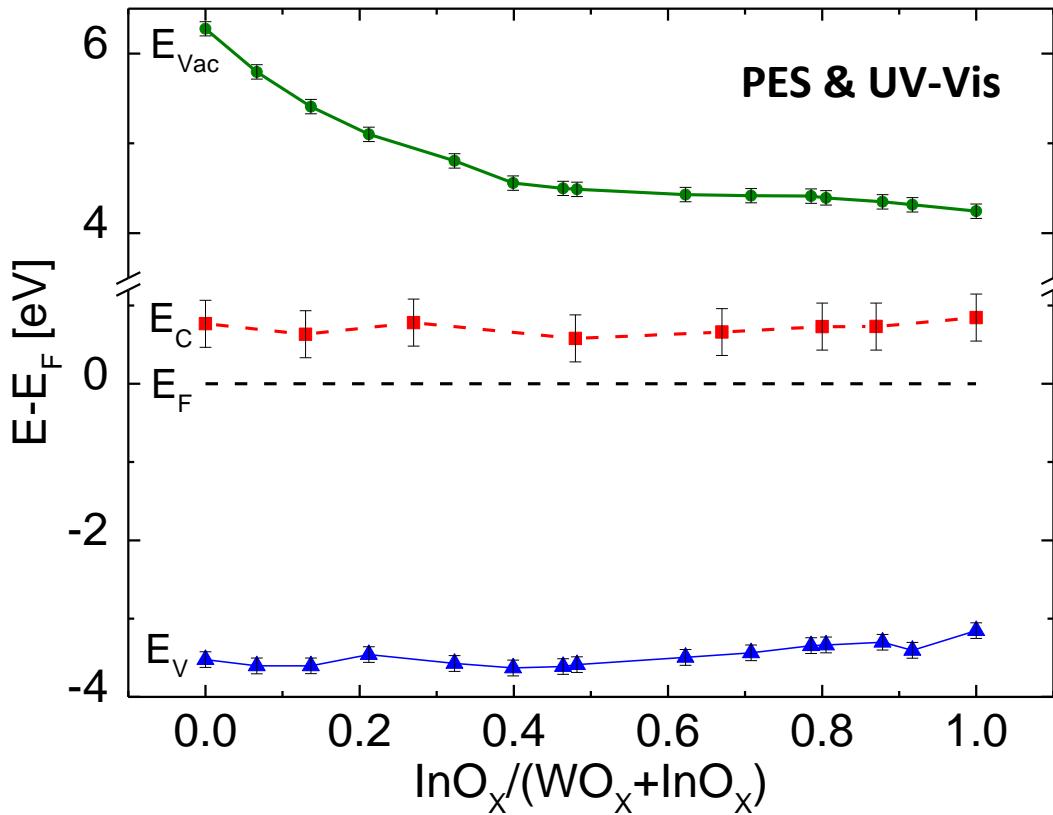
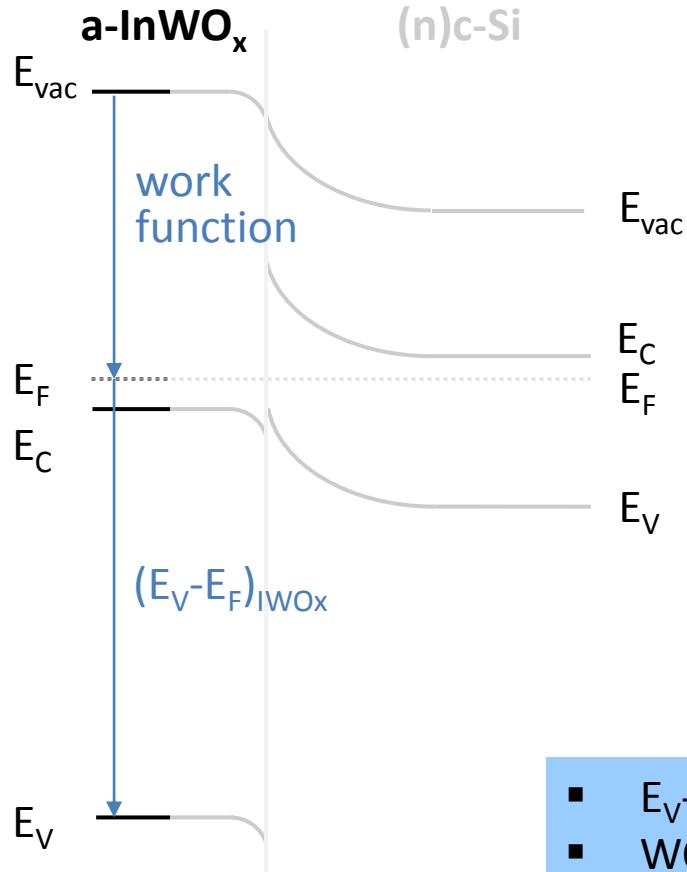
## XPS core level spectroscopy

W 4f, In 3d<sub>3/2</sub> & O 1s core levels



- HF dip
- load into MBE ( $p \sim 10^{-9}$  mbar)
- thermal co-evap. of  $\text{WO}_x + \text{InO}_x$
- no intentional heating  
→ **amorphous  $\text{IWO}_x$**
- **in-system** photoelectron spectroscopy

In the dark, at equilibrium

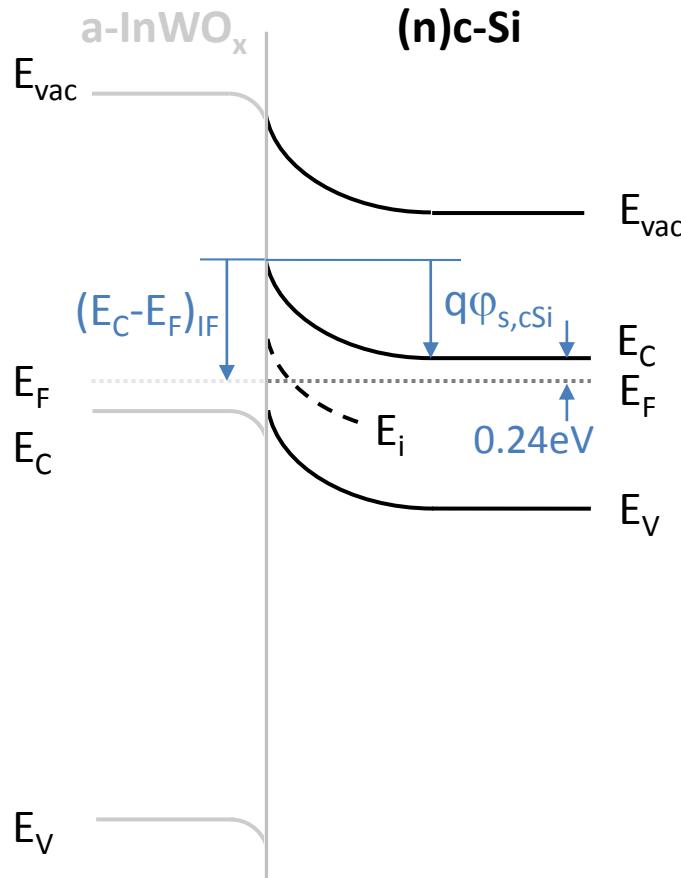


- $E_V - E_F = 3.2 \dots 3.6 \text{ eV}$
- $\text{WO}_x \rightarrow \text{InO}_x: E_g = 4.3 \dots 4.0 \text{ eV}$  (Tauc, direct, allowed) \*
- a-InWO<sub>x</sub> probably *not* degenerately doped

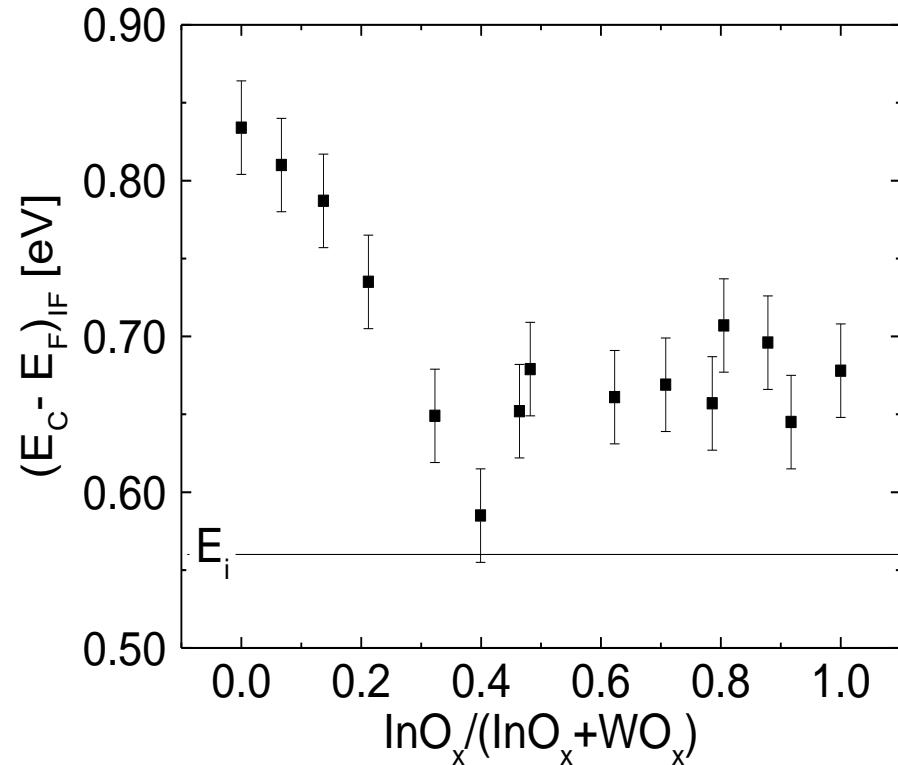
\*  $\text{WO}_x: E_g \sim 2.6 \dots 3.5 \text{ eV}$  (Granqvist, Sol. En. Mat. 2000);

$\text{In}_2\text{O}_3: E_{g,\text{direct}} \sim 3.6 \text{ eV}$  (Liu, JAP, 2008) 33

In the dark, at equilibrium

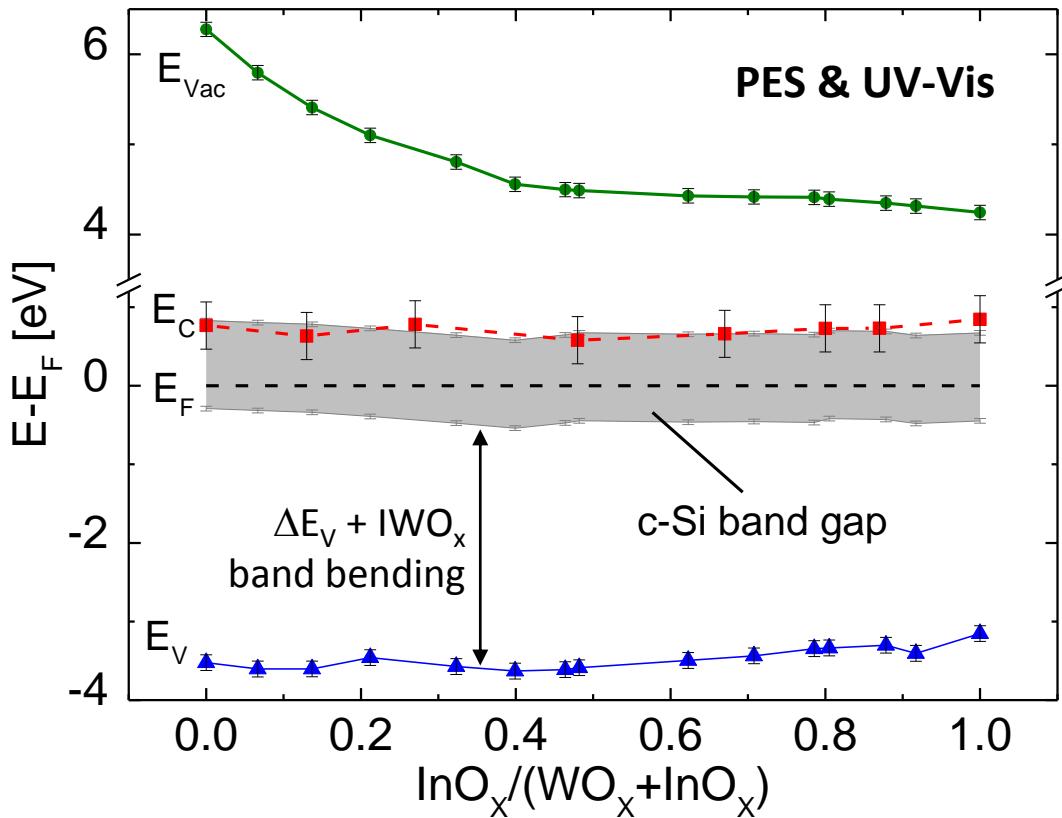
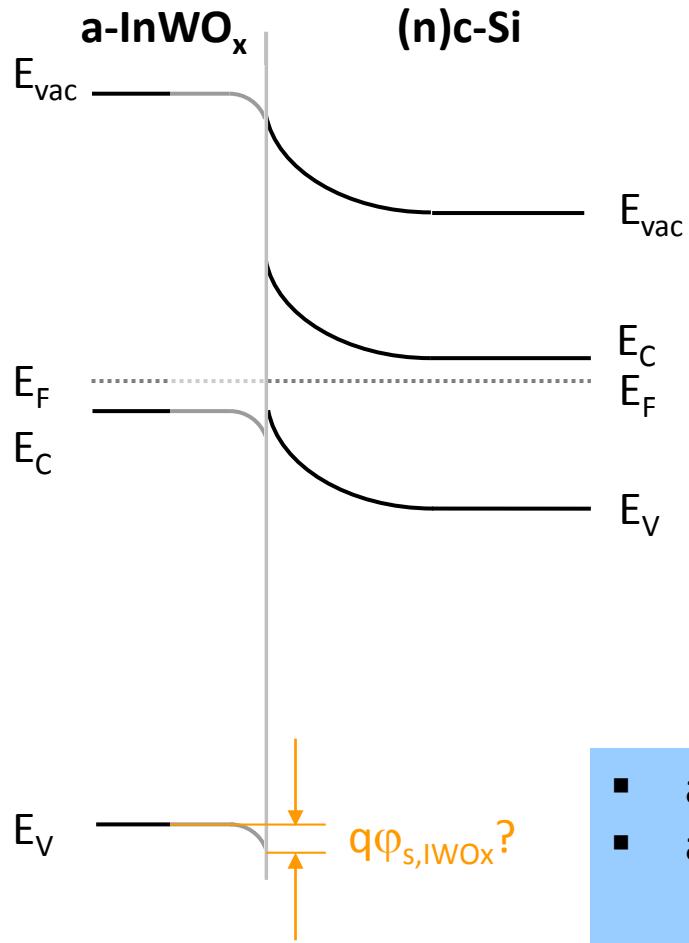


Barrier for electrons:  
 $(E_C - E_F)_{bulk} + q\varphi_{s,cSi}$  from surface photovoltage



- Inversion (accumulation of holes) for all stoichiometries

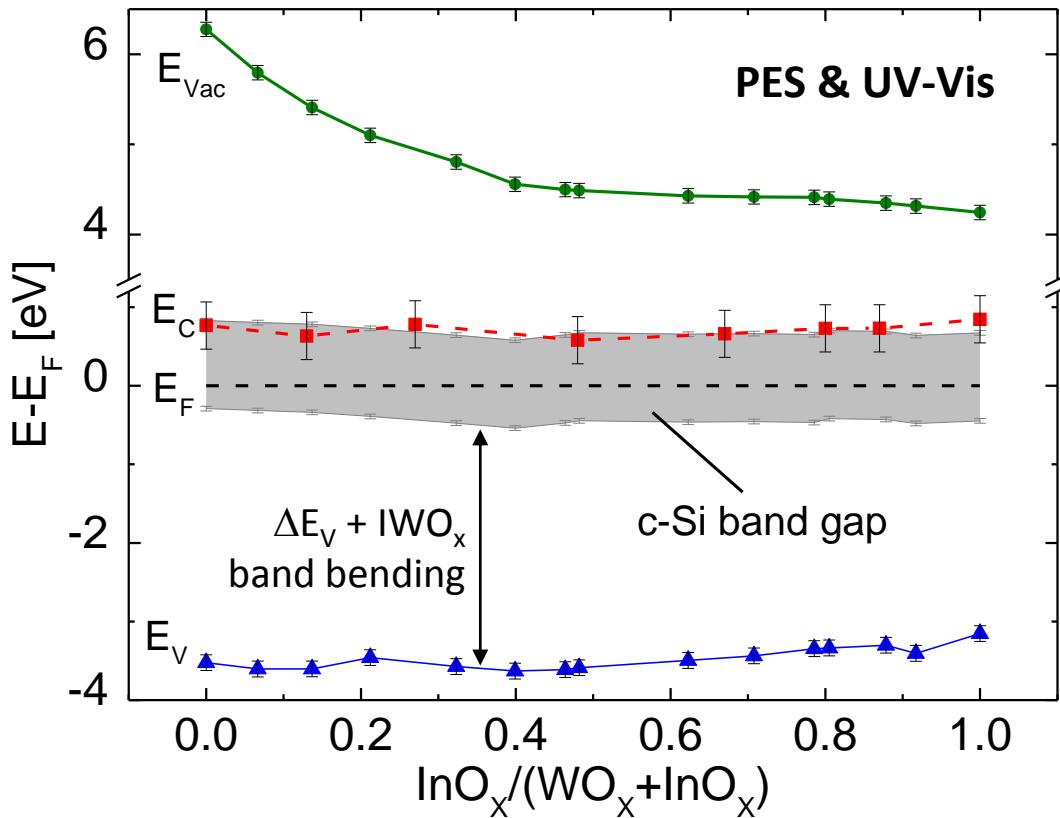
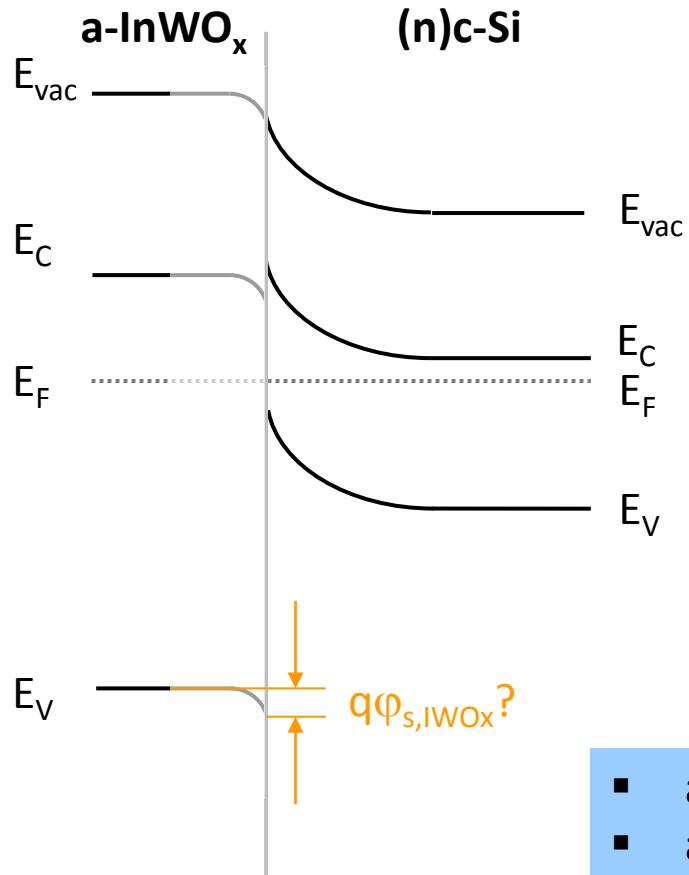
In the dark, at equilibrium



- a-IWOx/c-Si: staggered (type II) heterojunction
  - a-WO<sub>x</sub> → a-InO<sub>x</sub>:
    - $\Delta E_V = 3.3 \dots 2.7 \text{ eV}^*$
    - $\Delta E_C \approx 0 \text{ eV}$
- $\left. \right\} + \text{band bending } q\varphi_{s,\text{IWOx}}$

\* Theory: bcc-In<sub>2</sub>O<sub>3</sub>  $\Delta E_V = 3.2 \text{ eV}$  (Höffling, APL, 2010) Exp.: a-InO<sub>x</sub>, photoinjection:  $\Delta E_V = 2.6 \text{ eV}$  (Schmidt, 2007)

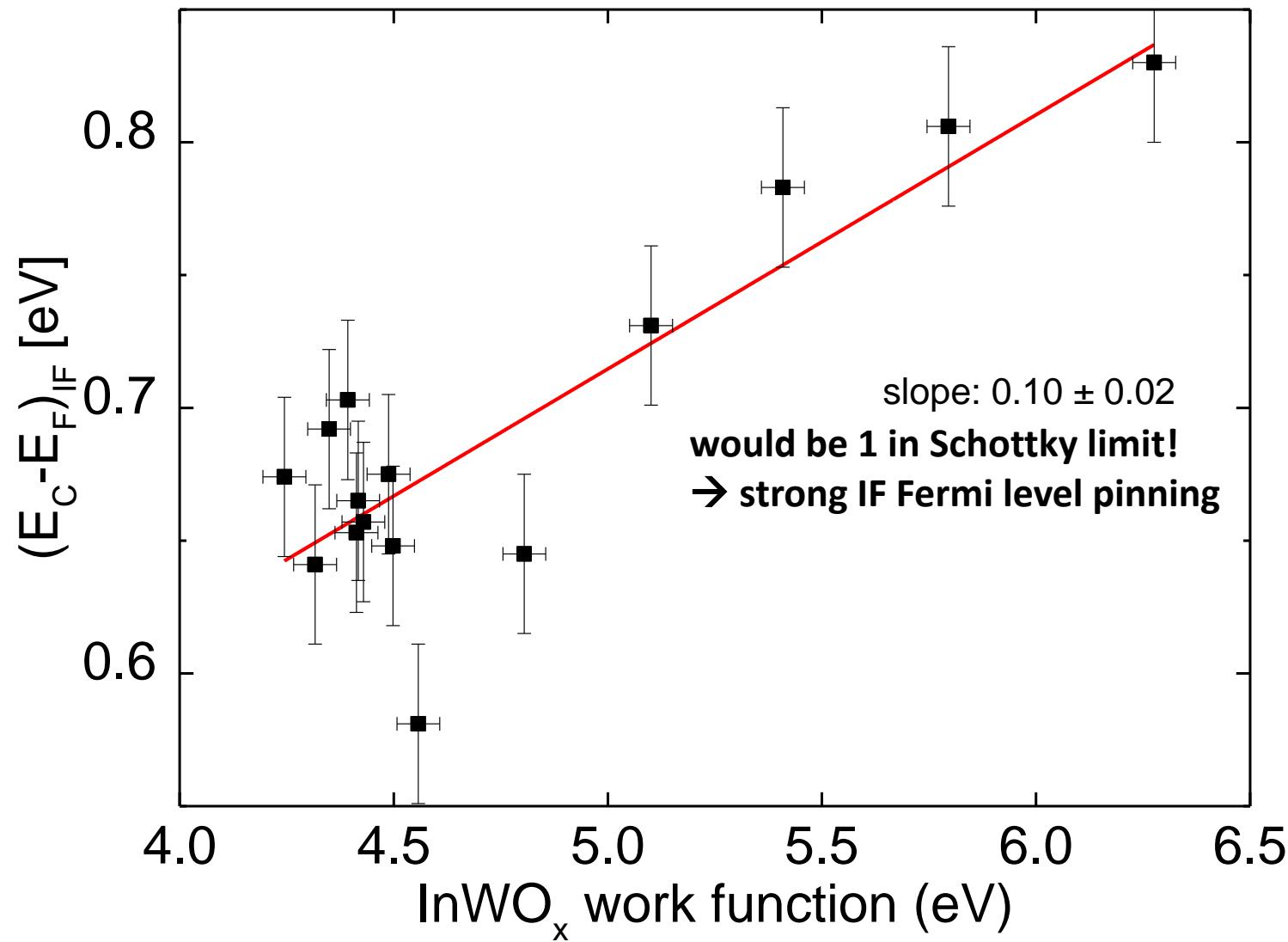
In the dark, at equilibrium

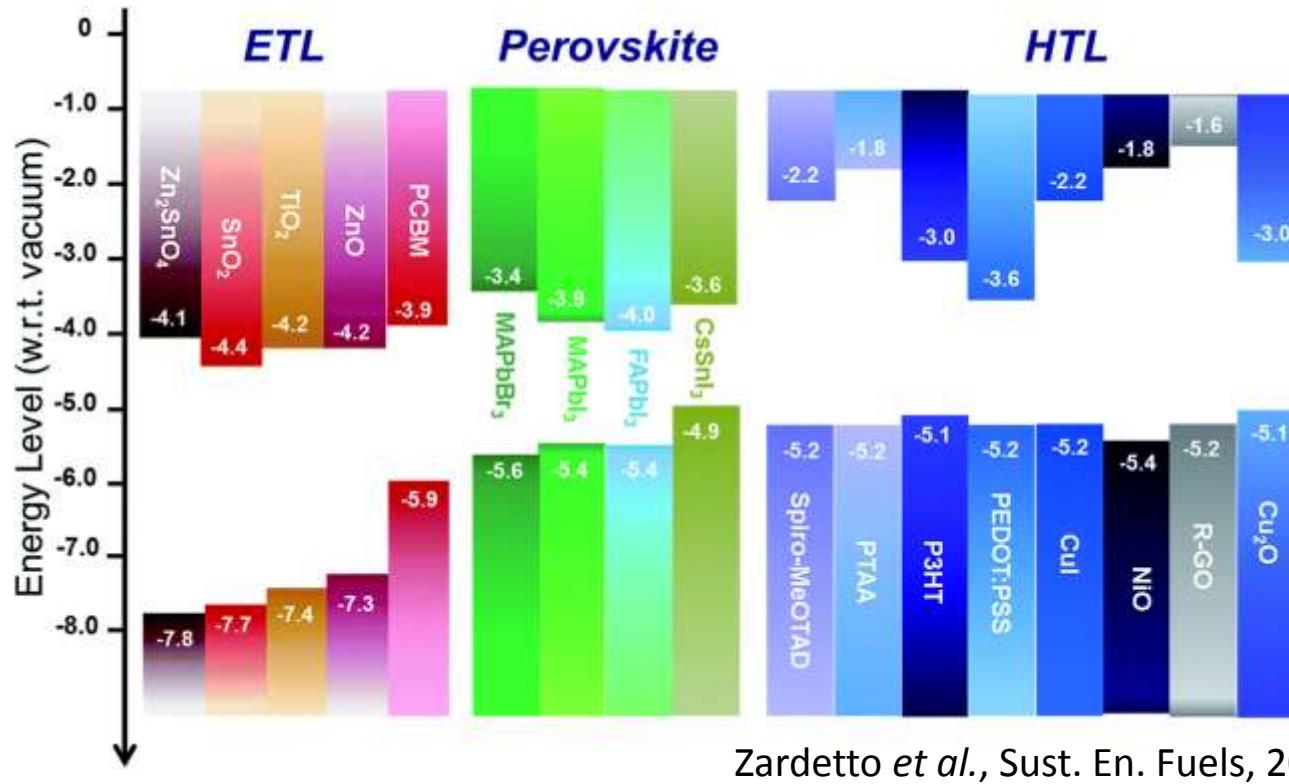


- a-IWOx/c-Si: staggered (type II) heterojunction
  - a-WO<sub>x</sub> → a-InO<sub>x</sub>:
    - $\Delta E_V = 3.3 \dots 2.7 \text{ eV}^*$
    - $\Delta E_C \approx 0 \text{ eV}$
- } + band bending  $q\varphi_{s,\text{IWO}_x}$

\* Theory: bcc-In<sub>2</sub>O<sub>3</sub>  $\Delta E_V = 3.2 \text{ eV}$  (Höffling, APL, 2010) Exp.: a-InO<sub>x</sub>, photoinjection:  $\Delta E_V = 2.6 \text{ eV}$  (Schmidt, 2007)

# Interface Fermi level pinning





## Band line-up considerations in OPV and perovskites(?)

- “Anderson’s rule”:  $\Delta E_C = \chi_A - \chi_B$ ,  $\Delta E_V = I_A^* - I_B^*$
- Schottky limit: no interface defects – no Fermi level pinning

**Usually not true for anorganic heterojunctions!**  
(but theories exist: charge neutrality levels, ...)

## *Passivating carrier-selective contacts*

### *Basic requirements*

- Passivation (or non-existence) of interface defects
- Energy band alignment: aligned band edges vs. barriers
- Optical transparency
- (high electronic conductivity)

### *“Classical” example for CSCs: Si heterojunction cells*

- well-passivated interfaces → low recombination →  $V_{oc} > 700\text{mV}$

### *Novel carrier-selective contacts*

- From OPV & microelectronics community:  $\text{MoO}_x$ ,  $\text{WO}_x$ ,  $\text{V}_2\text{O}_5$ , ...

### *Example: Thermally evaporated InWO<sub>x</sub>*

- $\text{InWO}_x/(n)\text{-Si IF}$  inverted for all stoichiometries
- c-Si band bending  $> 0.5 \text{ eV}$  for  $\text{InO}_x/\text{InWO}_x = 0\dots20\%$
- Type II heterojunction,  $\Delta E_v = 3.3\dots2.7 \text{ eV}$ ,  $\Delta E_c \sim 0\text{eV}$  ( $\pm \text{InWO}_x$  b.b.)

## Textbooks & monographs

- P. Würfel, *Physics of Solar Cells*. New York, NY, USA: Wiley (2009)
- W. Mönch, Electron. Prop. of Semiconductor Interfaces, Springer (2004)

## Carrier selective contacts & band line-up

- U. Würfel et al.: Charge Carrier Separation in Solar Cells. *IEEE J. Photovolt* **5** (2015) 461
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- J. Tersoff: Theory of semiconductor heterojunctions: The role of quantum dipoles. *Phys. Rev. B*, **30** (1984) 4874
- A. Klein et al.: Transparent Conducting Oxides for Photovoltaics: Manipulation of Fermi Level, Work Function and Energy Band Alignment. *Materials* **3** (2010) 4892-4914

## Numerical simulations of heterojunctions

- AFORS-HET, [https://www.helmholtz-berlin.de/forschung/oe/ee/sipv/projekte/asicsi/afors-het/index\\_en.html](https://www.helmholtz-berlin.de/forschung/oe/ee/sipv/projekte/asicsi/afors-het/index_en.html)

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...and all colleagues at **HZB Inst. Silizium-Photovoltaik, PVcomB, Young Investigator Groups Albrecht & Unger**

## Financial Support:

 **HERCULES** – EU FP7 project no. 608498

 **NEXTBASE** - EU H2020 project no. 727523  
THE NEXT GENERATION BASELINE

**HERA** – German BMWi project

**PersiST** – German BMWi project